

Advanced Large Area Deposition using Focused Beam Sources

**Surface Optics Corp
SCCAVS May 15, 2012
Michael L. Fulton**



Presentation Outline

- ◆ **Introduction: Including a biographical synopsis**
- ◆ **Coating Processes: PVD and energetic (IAD)**
- ◆ **3.3 Meter Diameter Chamber**
- ◆ **Kepler Primary Mirror Coating**
- ◆ **Next Generation Large Chamber**
- ◆ **Filtered Cathodic Arc**



Brief Biography

- ◆ Optical Coating Laboratory Inc. (OCLI): 1973 to 1989
 - Process Engineering; First end-Hall ion source in production
- ◆ PSI Max Optics Inc. 1989 to 1990
 - Developed DWDM coating system—OCA / Corning Prototype
- ◆ Boeing High Technology Center: 1990 to 1993
 - World Record Space Solar Cell; IAD Development
- ◆ Avimo Singapore Ltd. 1993 to 1997
 - Filter Cathodic Arc; IAD; Night Vision; Center of Excellence
- ◆ ZC&R Coatings for Optics Inc. 1997 to 2000
 - High Out Put IAD; IFCAD; Space Station Window Program
- ◆ Rockwell Science Center 2000 to 2003
 - Laser Eye Protection; Mars Reconnaissance Orbiter
- ◆ Ion Beam Optics Inc. 2003 to 2010
 - SBIR Phase II Radiation Hardening of Space Solar Cell Covers
- ◆ Surface Optics Corp. 2010 to Present
 - Kepler Primary Mirror; Band Pass Filters for Hyperspectral Imaging; Membrane filters for Space Antennas



SOC Chambers for Vacuum Deposited Coatings



*Small R&D chamber (0.6 meter)
For Coating Development*



*1.2 meter (Optical
Monitoring, planetary)*



*1.8 meter (roll-to-roll, or motion
Controlled e-beam IAD)*



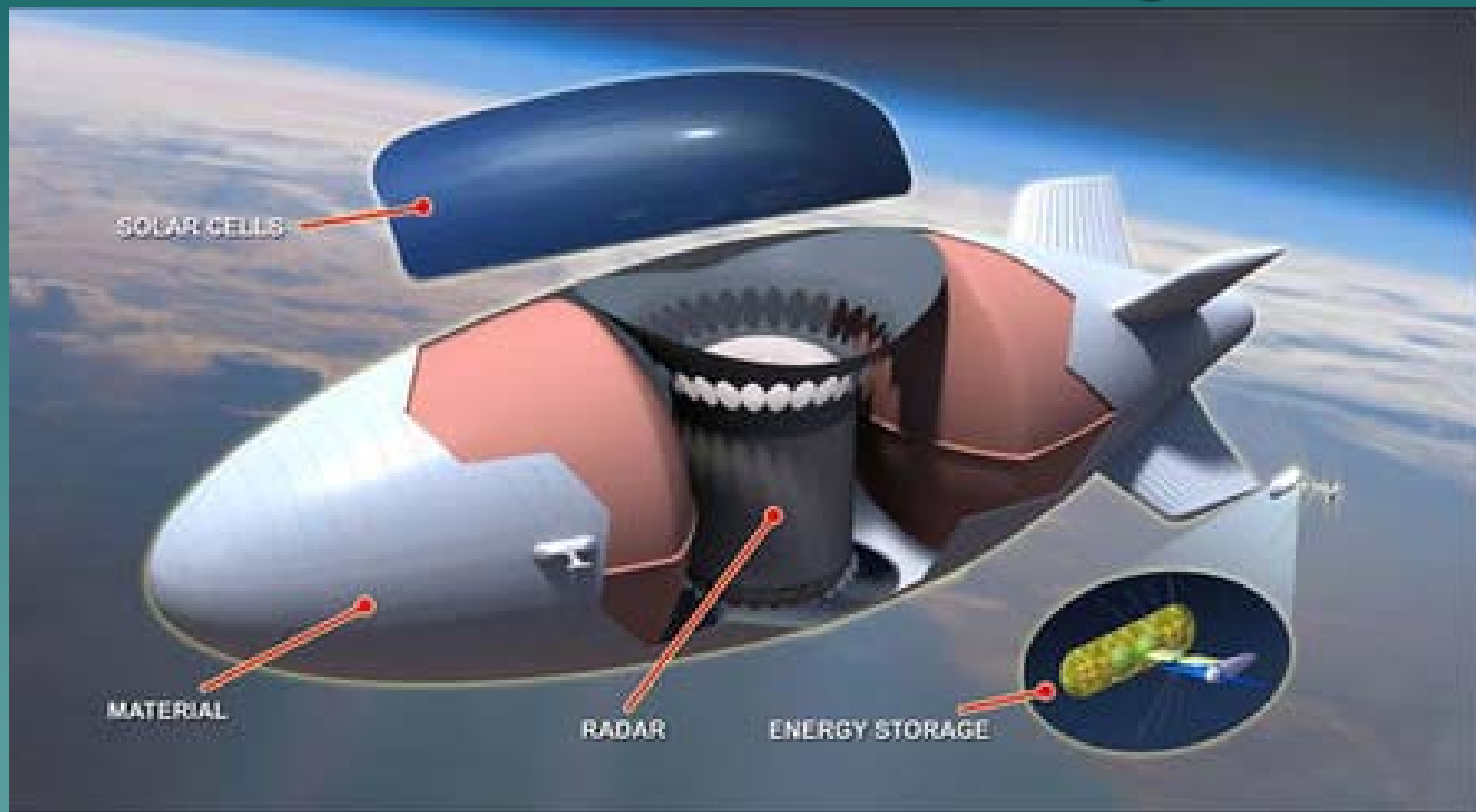
5 meter (roll-to-roll, e-beam IAD)



*3.3 meter (motion controlled
e-beam IAD)*

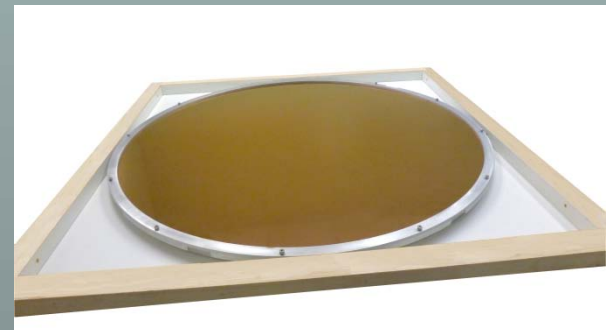


ISIS Surveillance Blimp Program: Thermal Control Coating





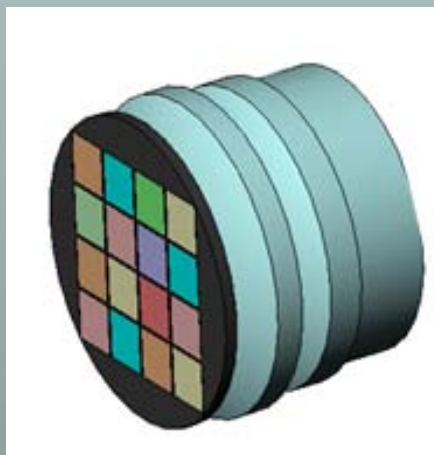
Membrane Coatings



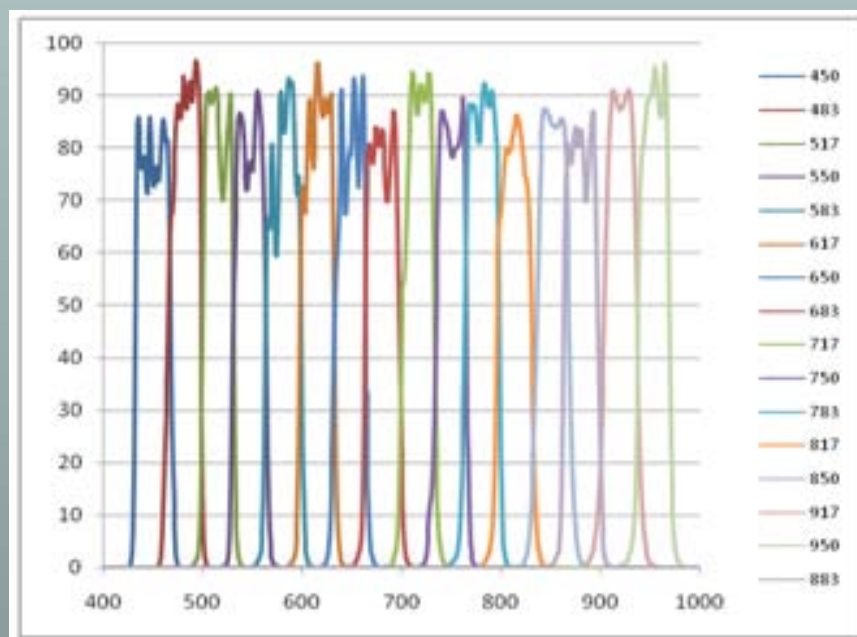


Macro Filter Array for Hyperspectral Cameras

- *Mosaic of narrow bandpass filters*
- *Vacuum deposit bandpass filters on wafer substrate*
- *Dice to size*
- *Assemble into mosaic filter array*



*Optical Filter Array,
16-Bands*



Filter Response Data



High-Energy Deposition Techniques Offer Advantages

- ◆ Ion Assisted Deposition (IAD) e-beam / thermal
- ◆ Plasma Assisted Deposition (PAD) Technology
- ◆ Magnetron Sputtering

- ◆ Improve the physical qualities of optical coatings:
 - ◆ Densify microstructure
 - ◆ Reduce defect density
 - ◆ Produce stoichiometrically correct compositions with stable optical properties
 - Index
 - Low k values



SainTech Source: Ion-Assisted-Deposition (IAD)



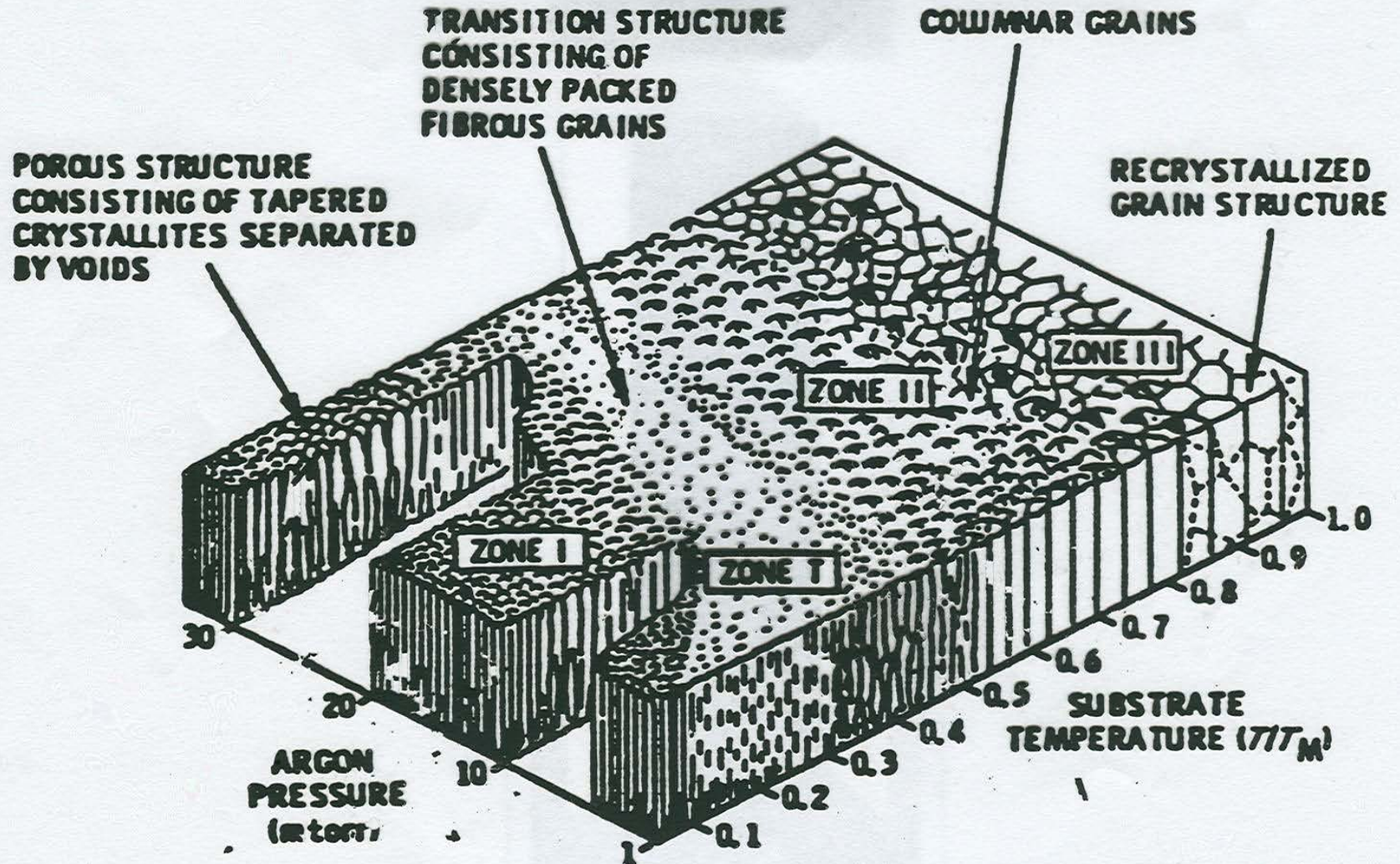


Ion Beam in Ion-Assisted-Deposition (IAD)



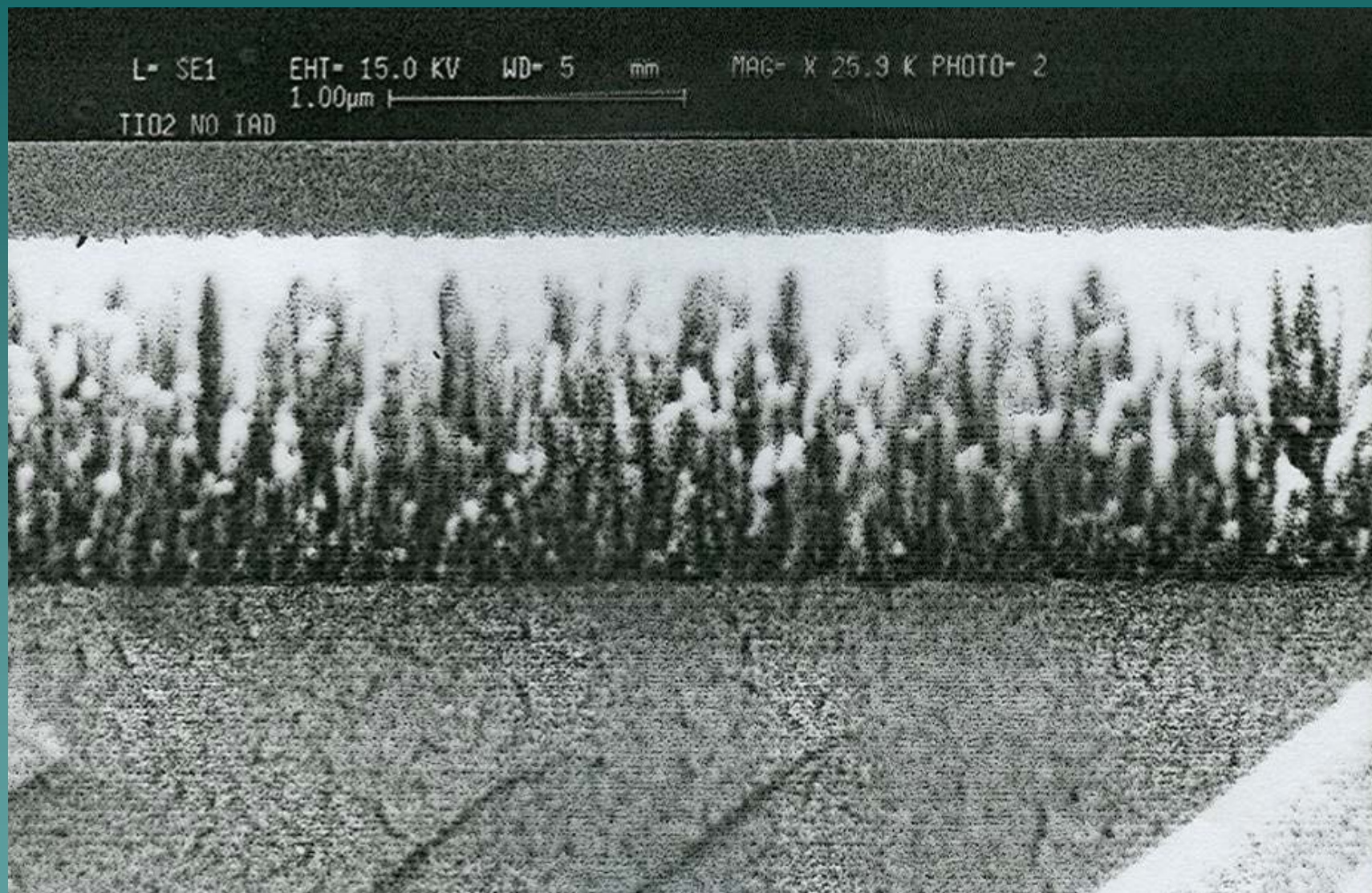


Thornton Film Growth Model (1974)



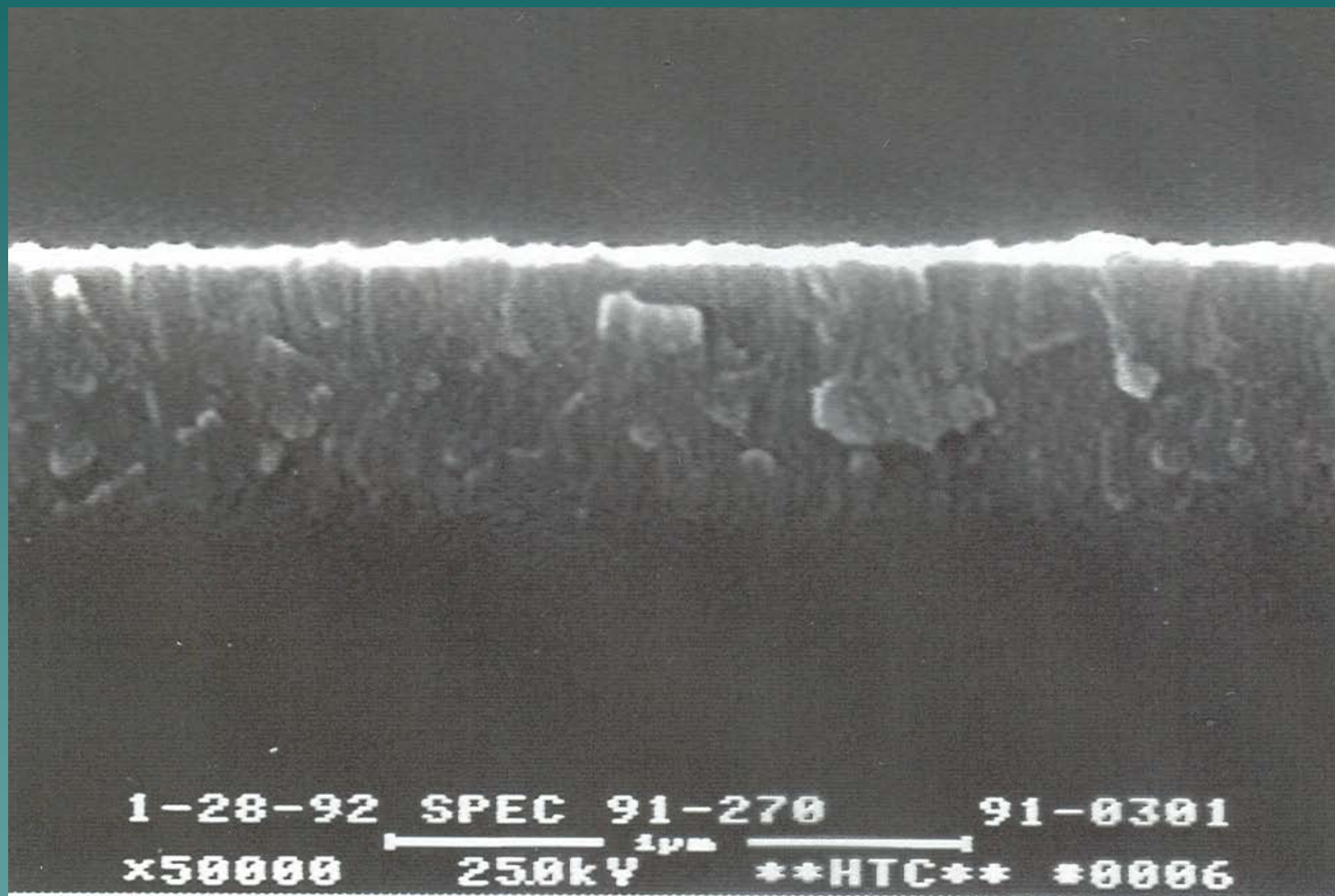


TiO₂ PVD Film Deposited at 300° C.





TiO₂ IAD Film Deposited at 50° C.





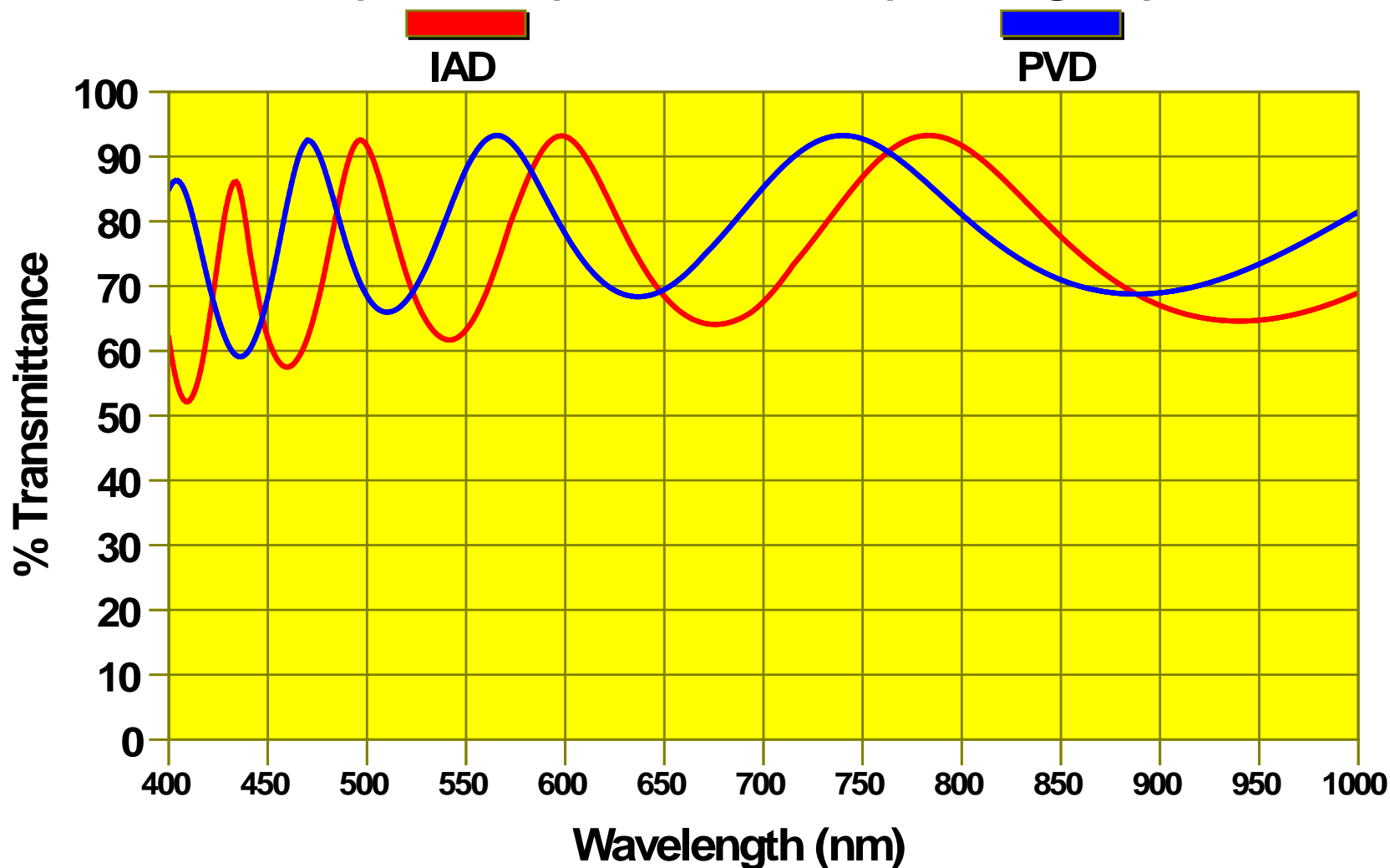
TiO₂ Optical Constants using IAD

• λ (nm)	n	k
• 300	2.85	.003
• 400	2.76	.005
• 500	2.55	.0003
• 600	2.47	
• 700	2.42	
• 800	2.41	
• 1000	2.40	
• PVD Process =	2.35 @ 500nm	



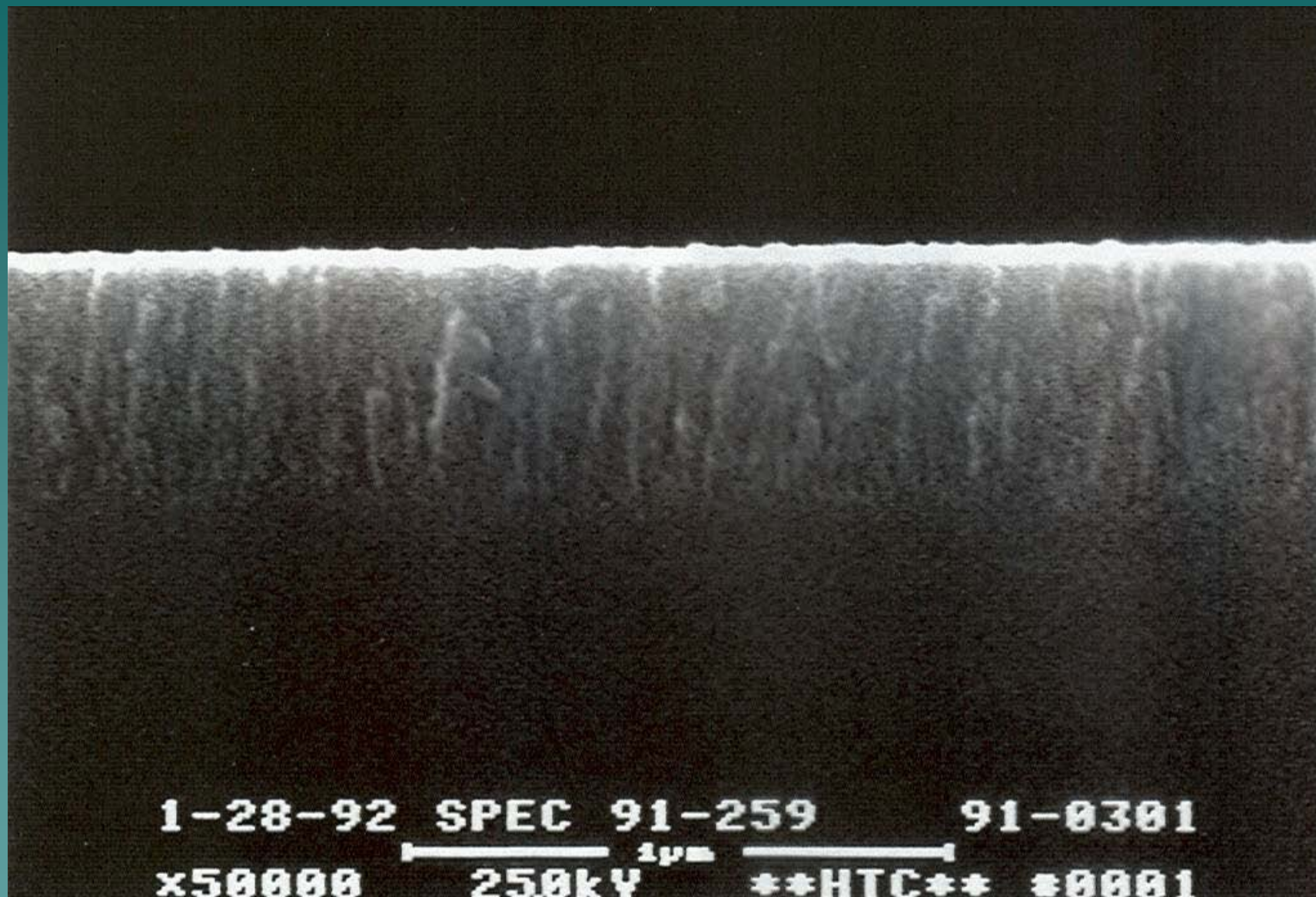
TiO₂ Optical Constants using IAD

IAD TiO₂ (Ambient) vs PVD TiO₂ (300 deg. C.)



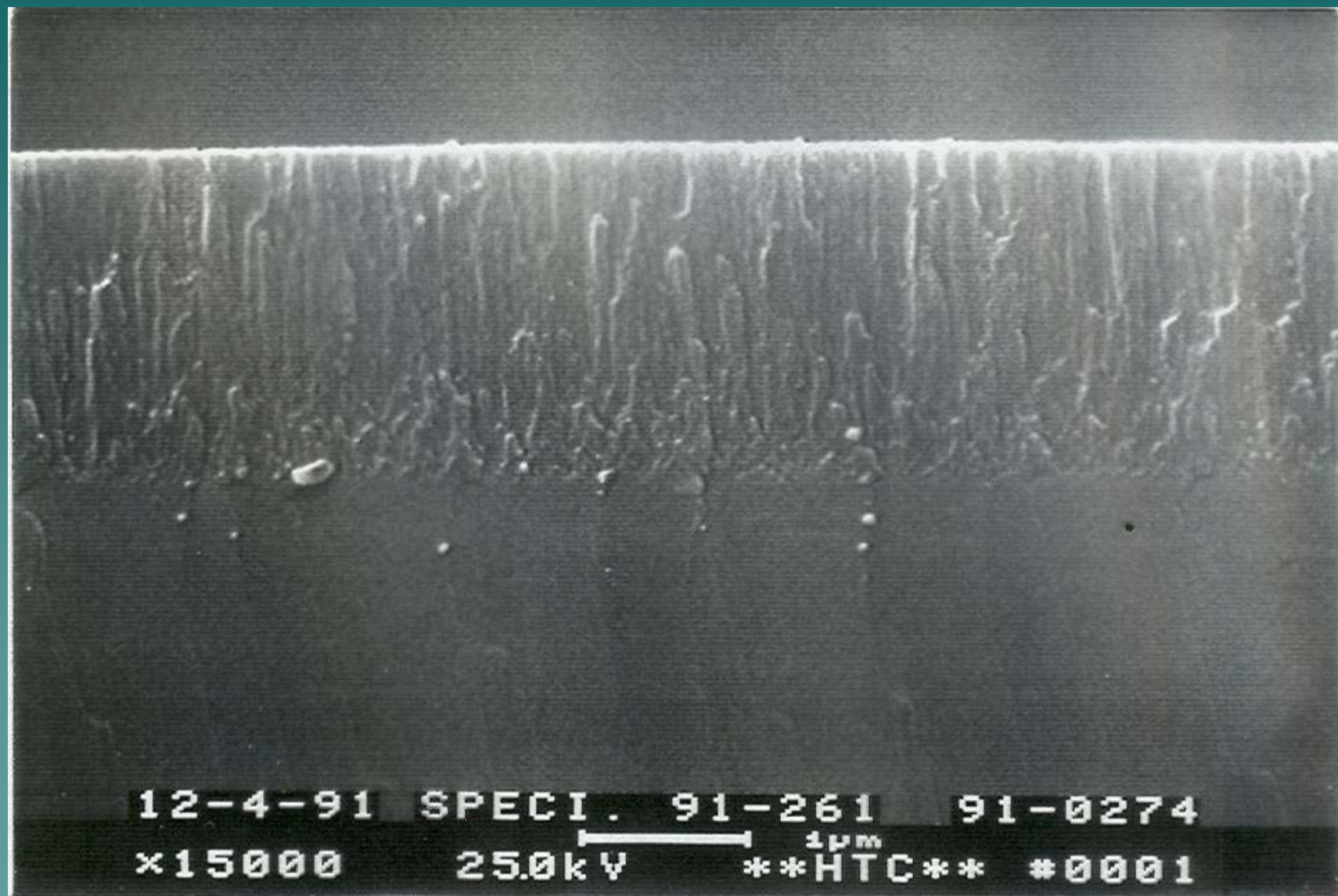


SiO_2 IAD Film Deposited at 50° C.



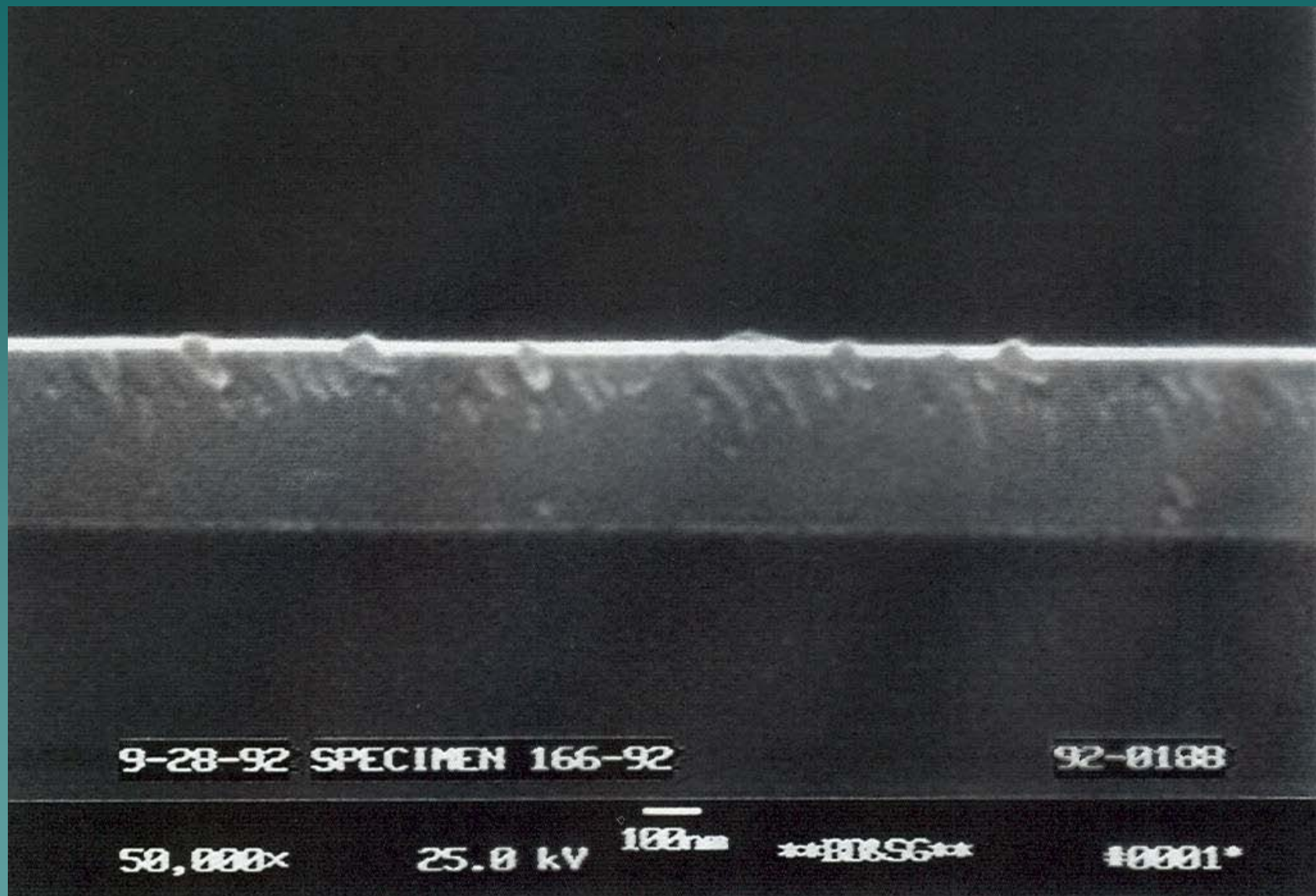


Al_2O_3 IAD Film Deposited at 50° C.





Si_3N_4 IAD Film Deposited at 50° C.





Ion Assisted Deposition Summary

- **Temperature: Second Order Effect**
- **Mechanical Properties: Improved Adhesion & Durability**
- **Optical Performance: Refractive Index Stability**
- **Manufacturing: Repeatability**
- **Temperature Sensitive Substrates**
- **Pulsed IAD: Fluoride Deposition at Ambient Substrate Temperature**



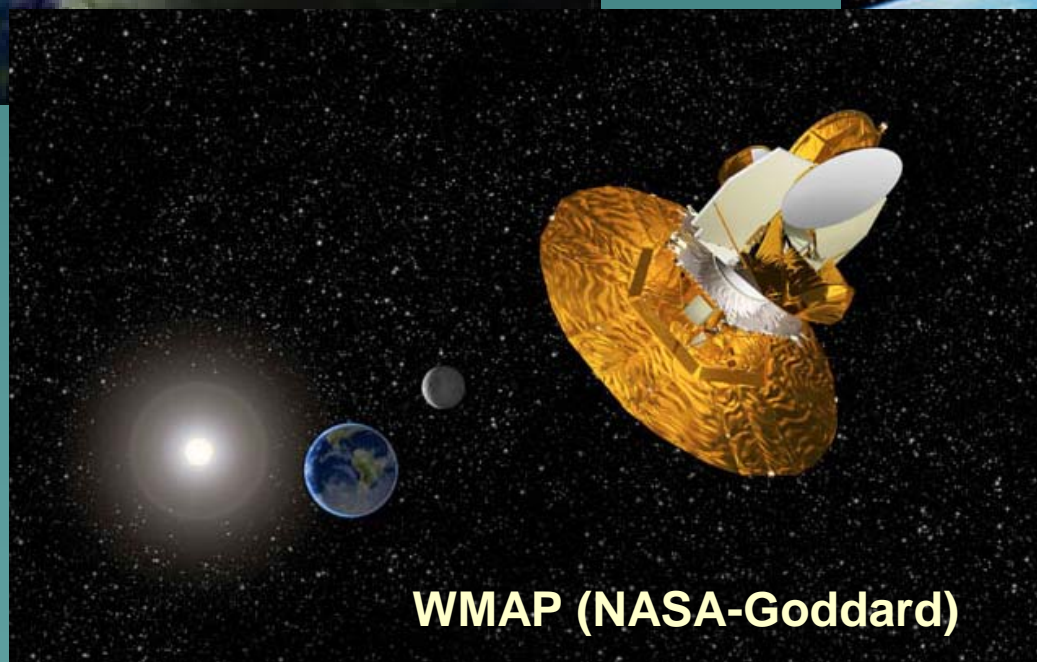
SOC Heritage...Spaceflight Reflectors



CloudSat (JPL)



**Commercial
Telecom Satellite
(Boeing)**



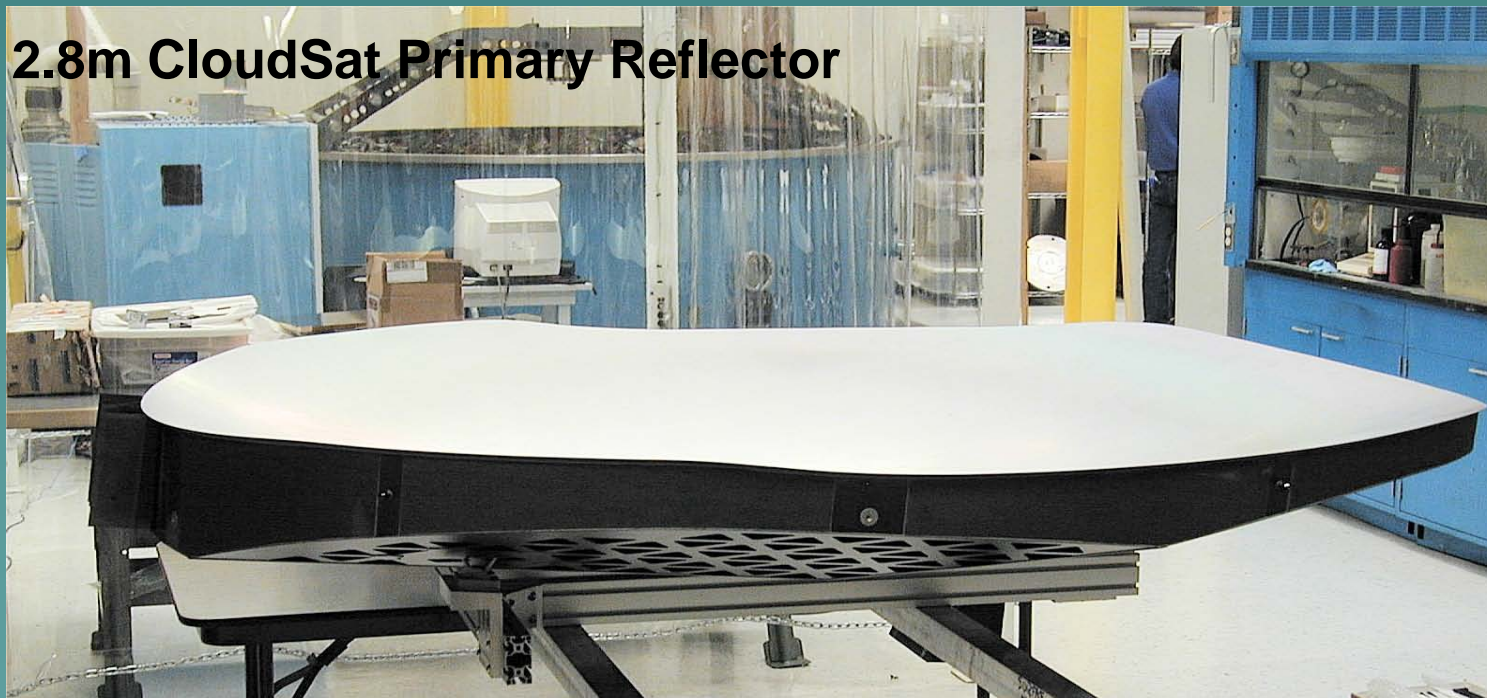
WMAP (NASA-Goddard)



Typical Reflector Requirements

Materials	Aluminum, Silicon Oxide (SiO _x or SiO ₂)
Thickness	20,000Å +/- 2,000Å
Size	1m < Diameter < 3m

2.8m CloudSat Primary Reflector





CLOUDSAT: CLIMATE SURVAYOR



Satellite Program to Monitor Climate and Weather from Space



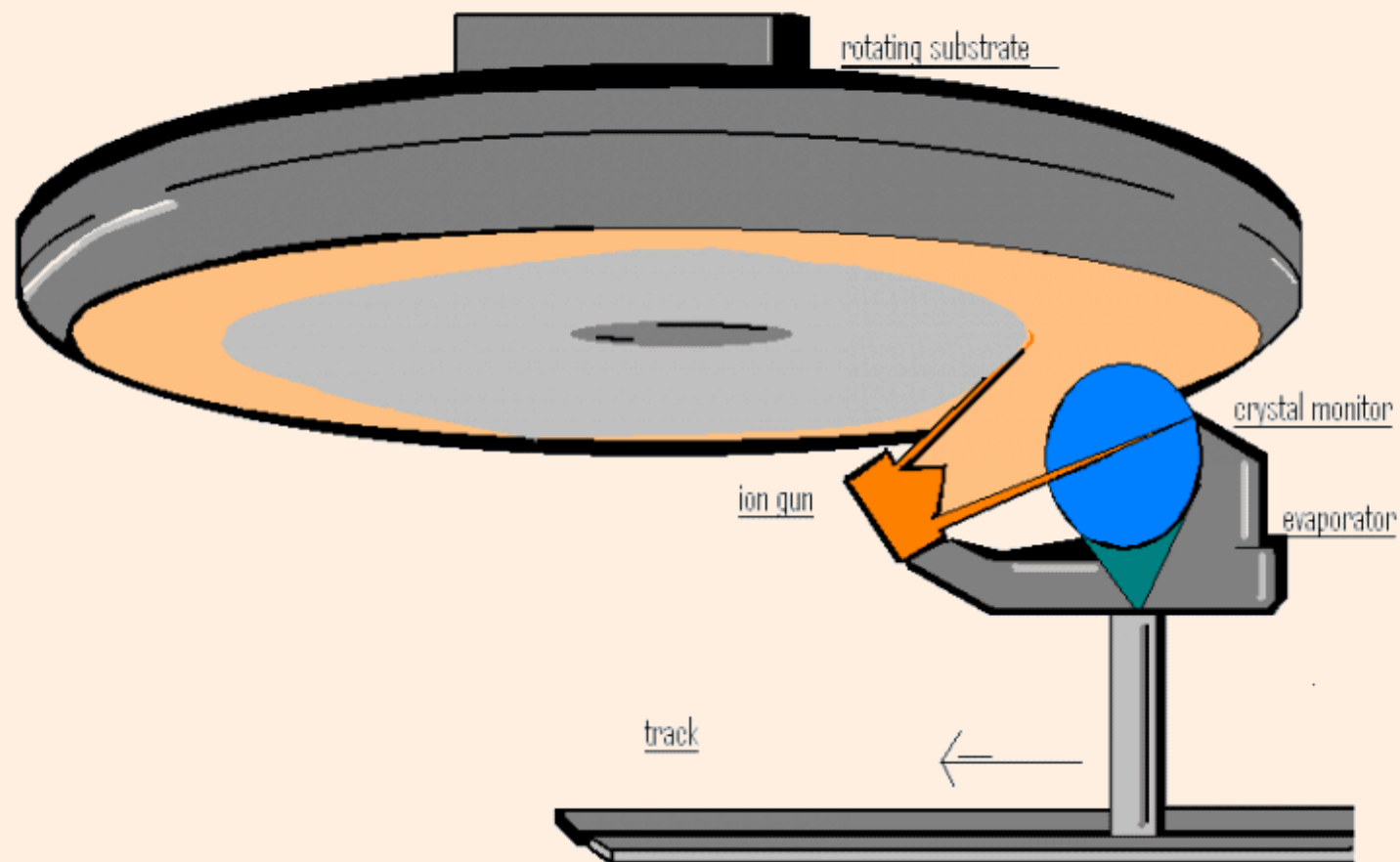
3.3m Diameter Vacuum Chamber Commissioned (2001)



← Fixture Diameter - 120 inches →



Animation of motion system





Moving Into Optical Coatings...

- ☑ Improvements in Thickness feedback and control
- ☑ Ion Assisted Deposition (IAD) was added for greater material & process versatility

NASA need: Space Qualified Silver

Reflectance	$R > 95\%$, 360nm to 2,000nm
Stress	Compatible w. lightweight substrate
Space Environment	Radiation, thermal cycling
Ground Environment	Humidity, T/C, cleaning, adhesion
Size (dia.)	Up to 2.5m, or multiple segments up to 1.5m



LLNL Protected Silver Design

L-Oxide	Reflection Enhancement Layers
H-Oxide	
L-Oxide	
H-Oxide	
L-Oxide	
Si_3N_4	Basic Protected Ag
Ni-CrN _x	
Ag	
Ni-CrN _x	
Substrate	

- ◆ Design developed & verified at LLNL.
- ◆ LLNL created nitride layers by sputtering NiCr and Si in presence of N⁺ ions.
- ◆ SOC developed process to produce nitride layers by IAD. (SBIR funding)
- ◆ NiCrN highly absorbing in blue/UV. Want to apply minimum thickness only.

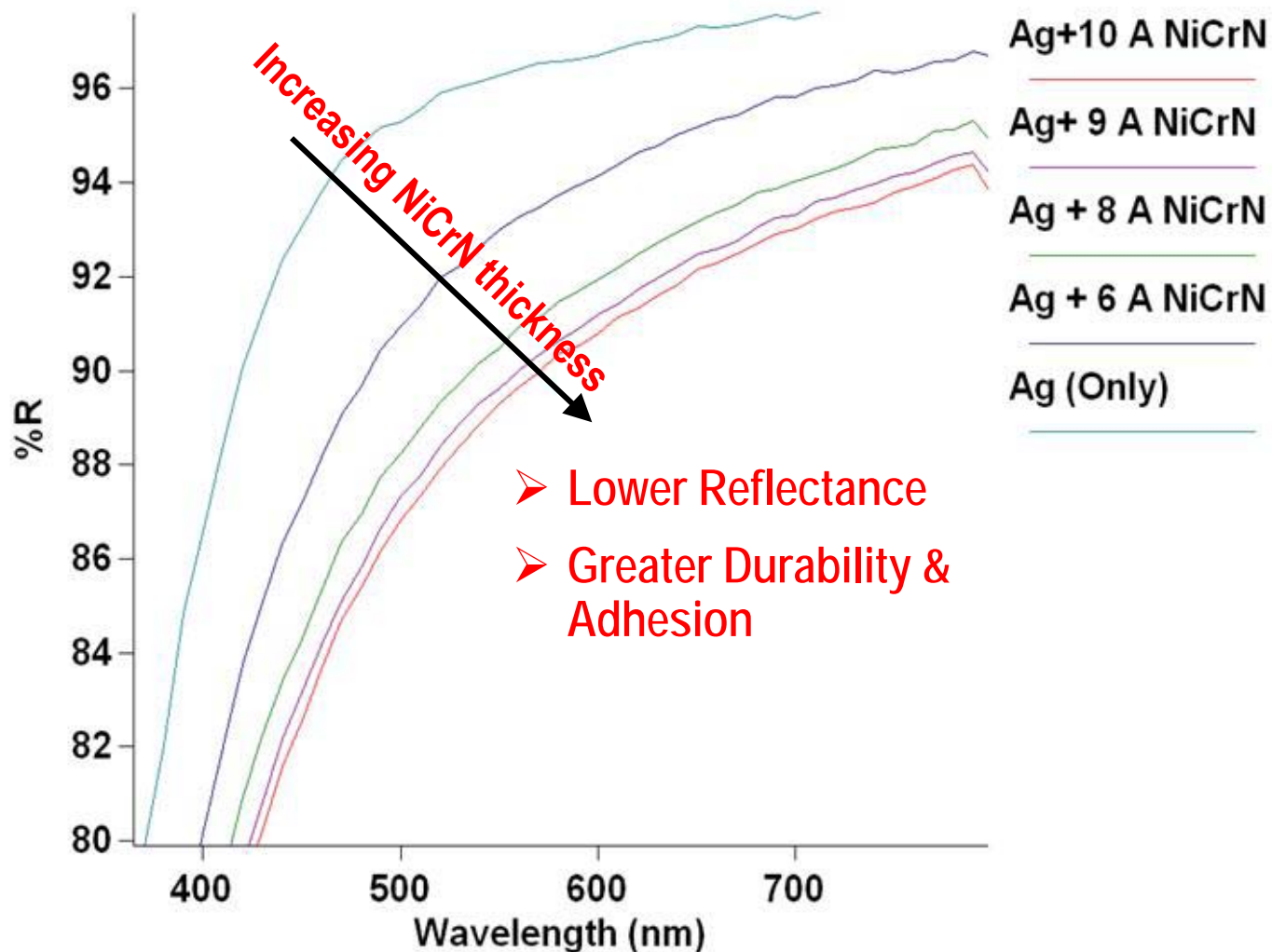


Why LLNL protection works?

- ◆ NiCrNx
 - Prevents Ag from reaction with S+
 - Promotes adhesion between Si₃N₄ and Ag
- ◆ Si₃N₄
 - Protects Ag from S+ and other chemical attack
 - Protects Ag from O+ during oxide deposition
- ◆ SiO₂/Ta₂O₅ pairs
 - Protect surface from scratching
 - Tailor to enhance reflectance in blue/UV



Effect of NiCrN thickness on Ag reflectance





LLNL Processing Challenges for Silver on Large Optics (Kepler)

- ◆ Precise deposition of 5Å of NiCrNx difficult over large areas.
- ◆ N+ bombardment of NiCr to make NiCrNx removes NiCr (had to compensate by adding extra NiCr to outer radial positions).
- ◆ Si₃N₄ easily contaminated with background gas (requires exceptional vacuum). Need for UHV slows cycle time between runs.
- ◆ Si₃N₄ has high index that reduces Ag reflectance.

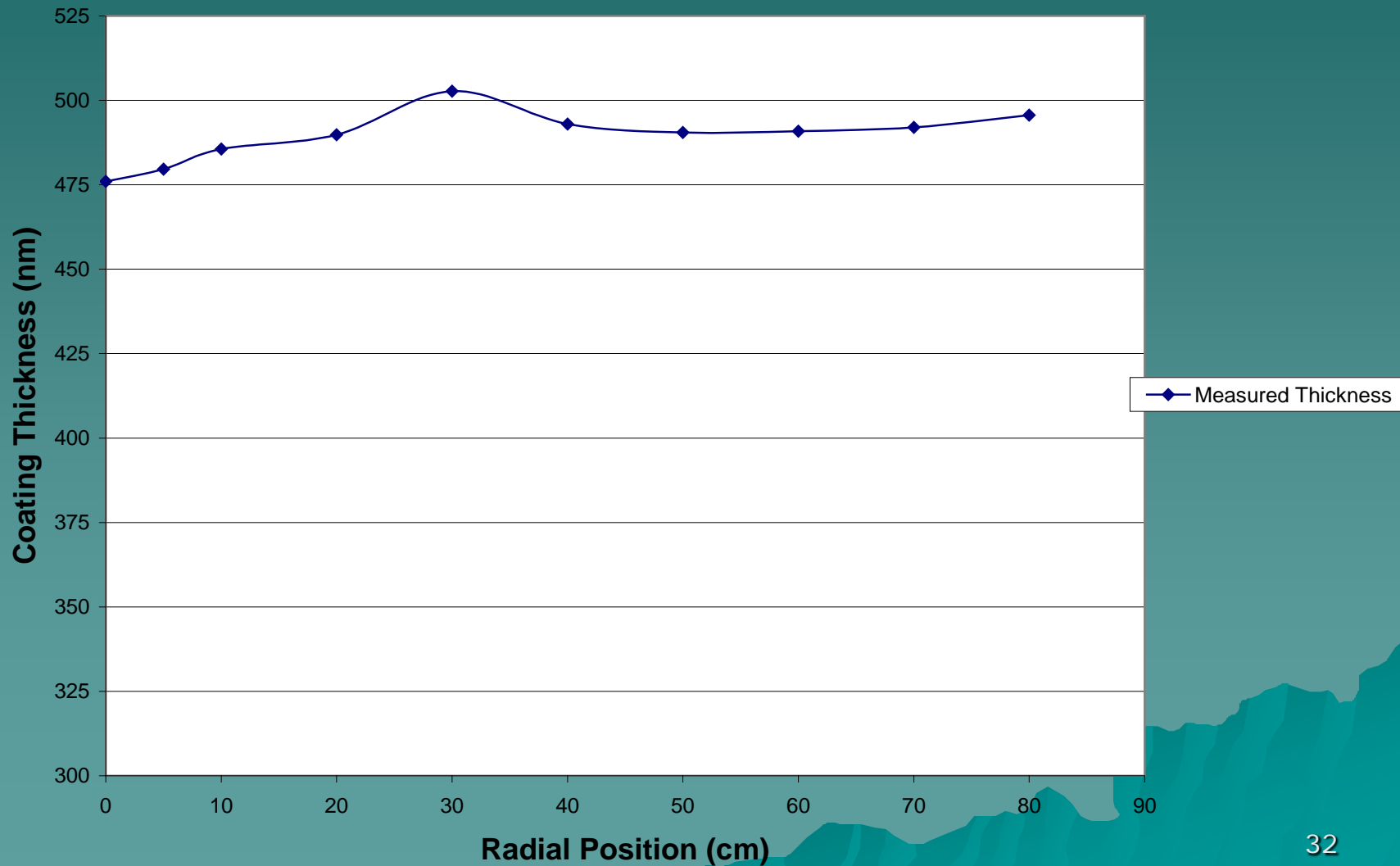


Processing Challenges for Large Optics (Kepler): Uniformity

- ◆ Deposition Uniformity of 5Å of NiCrNx difficult over large areas: e-beam / IAD plume control a huge challenge
- ◆ Si_3N_4 uniformity was also a challenge; Ag and the dielectrics were less troublesome
- ◆ General uniformity constraints: precision of translation stage movement; confinement of e-beam and resistance source plumes; center position sensitivity; and process repeatability.



Processing Challenges for Large Optics (Kepler): Uniformity



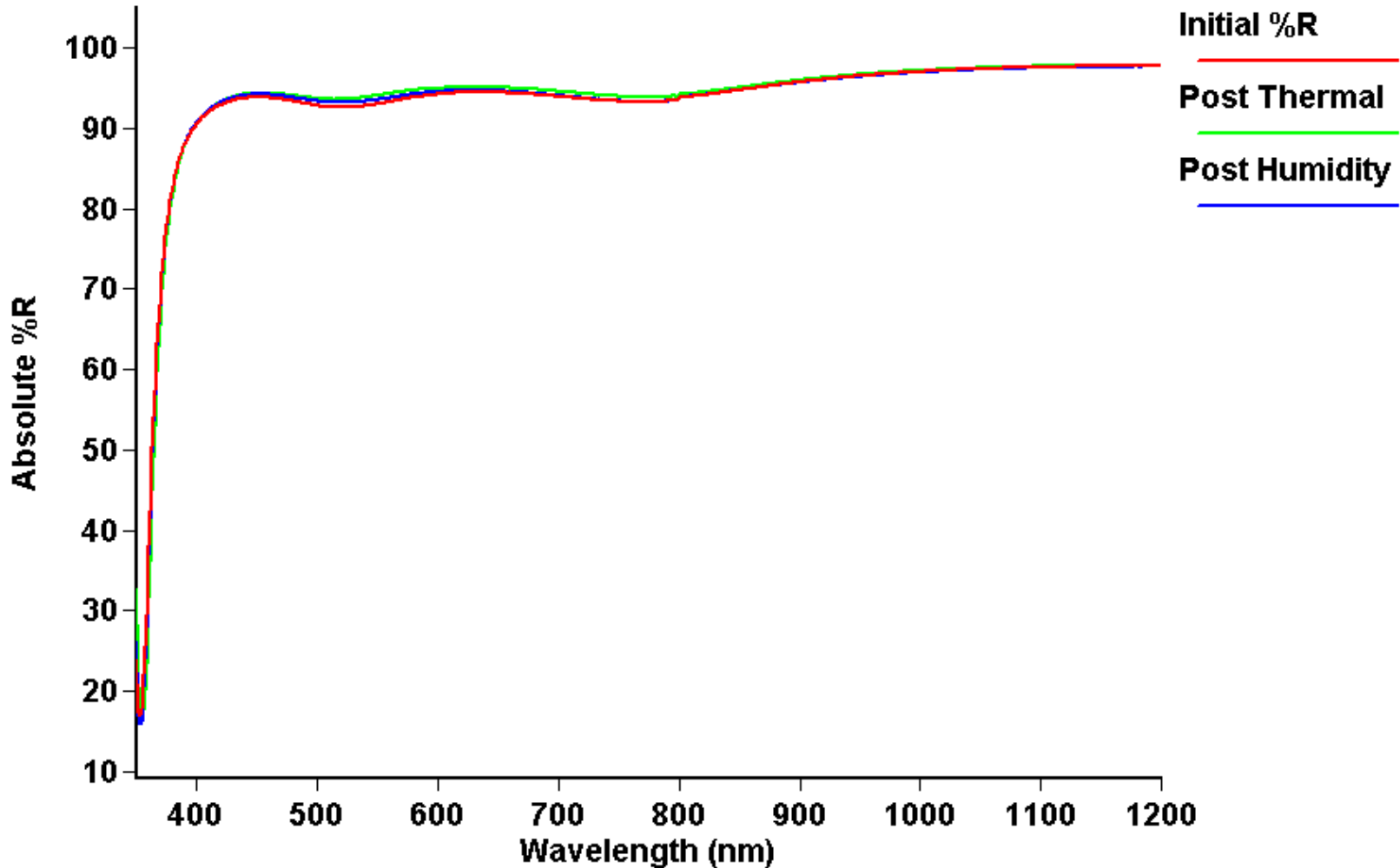


Processing Challenges for Large Optics (Kepler): Durability

- ◆ Durability requirements were driven primarily by the terrestrial exposure prior to launch
- ◆ The humidity test consisted of a 24-hour exposure at 50°C and 95% RH. The coating was thermally cycled 30 times from -80°C to +35°C and the reflectance was measured before and after each exposure test. Following environmental exposures, the coating passed MIL-13508C adhesion and moderate abrasion tests.
- ◆ Protected Ag Coating with Five-Layer HL Interference Coating; Passed Environmental Testing: Next Slide



Processing Challenges for Large Optics (Kepler): Durability



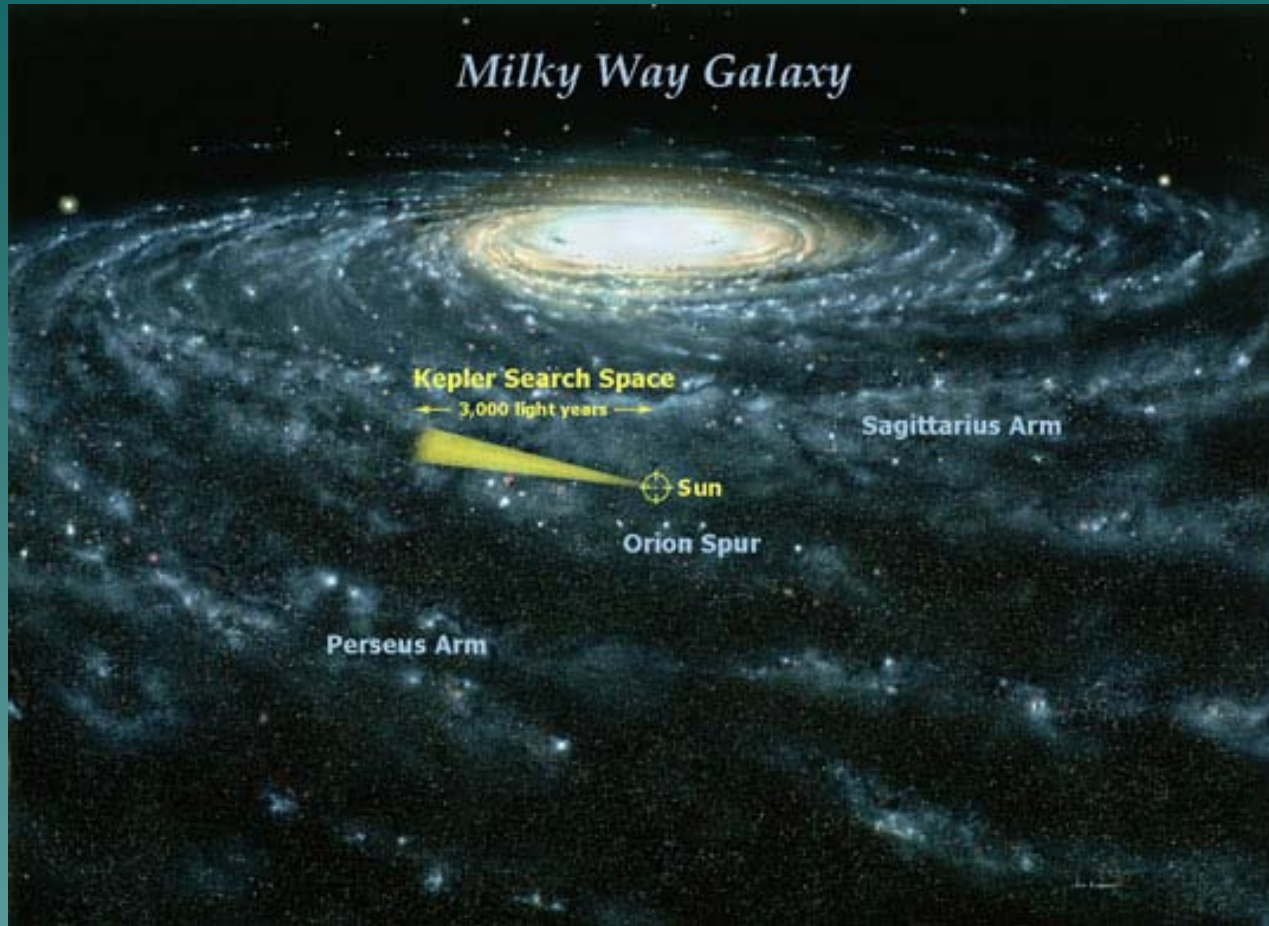


Processing Challenges for Large Optics (Kepler): Computer Control Improvements

- ◆ Old program ran on text files with relevant automation data; new version includes ability to generate text files from an updateable material data base.
- ◆ Program allows coating to deposit from the outside to inside (or, visa versa): thin layer rate is more controllable when source is already on.
- ◆ Others: Limit switches for home and start positions; run log file has overshoot data; computer control for translation stage stepper motor results in $< 1\%$ run-off across part.



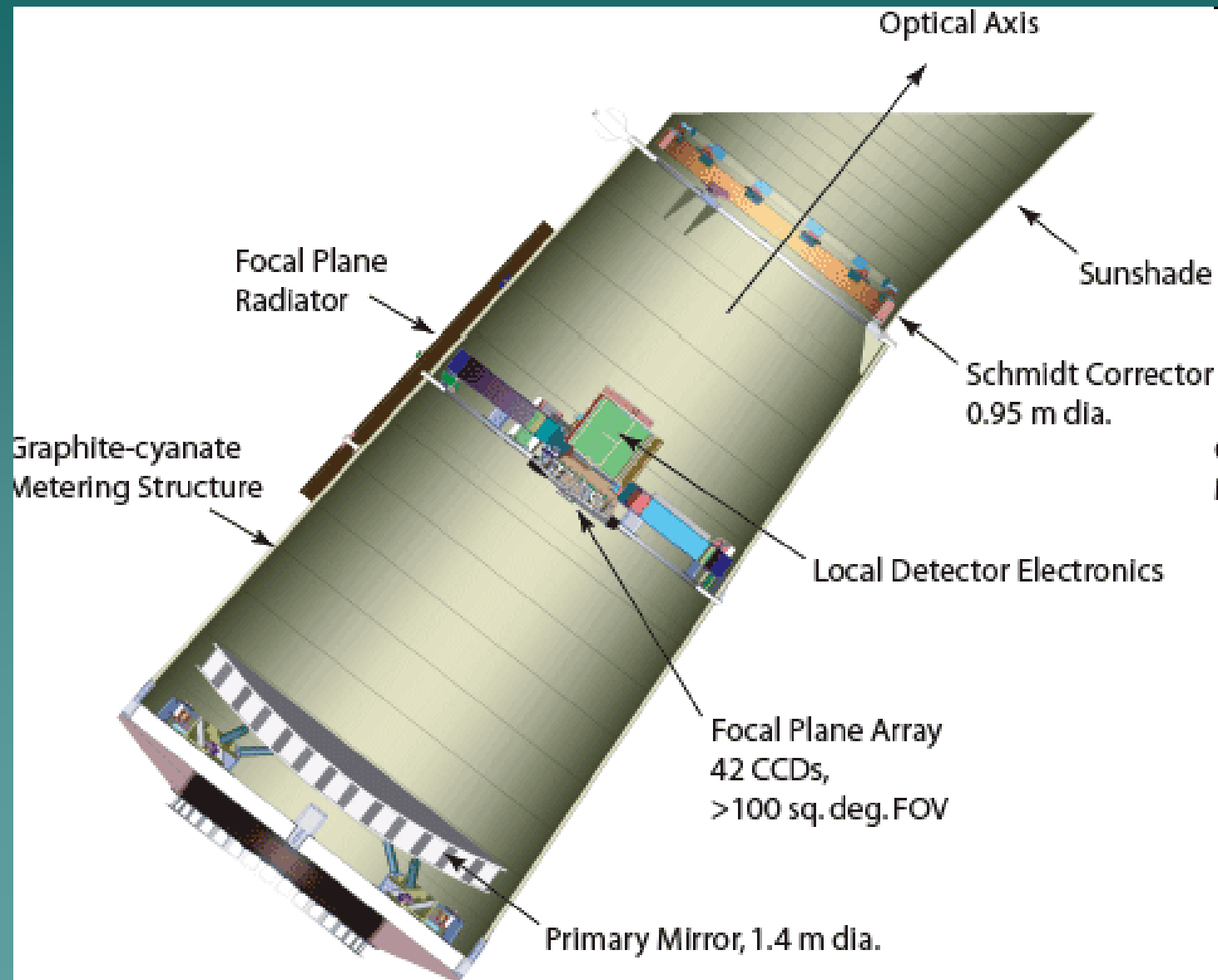
Kepler Mission



The Milky Way, showing our sun about 25,000 light years from the galaxy's centre. The yellow cone illustrates the region or 'starfield' in which Kepler hunts for habitable planets



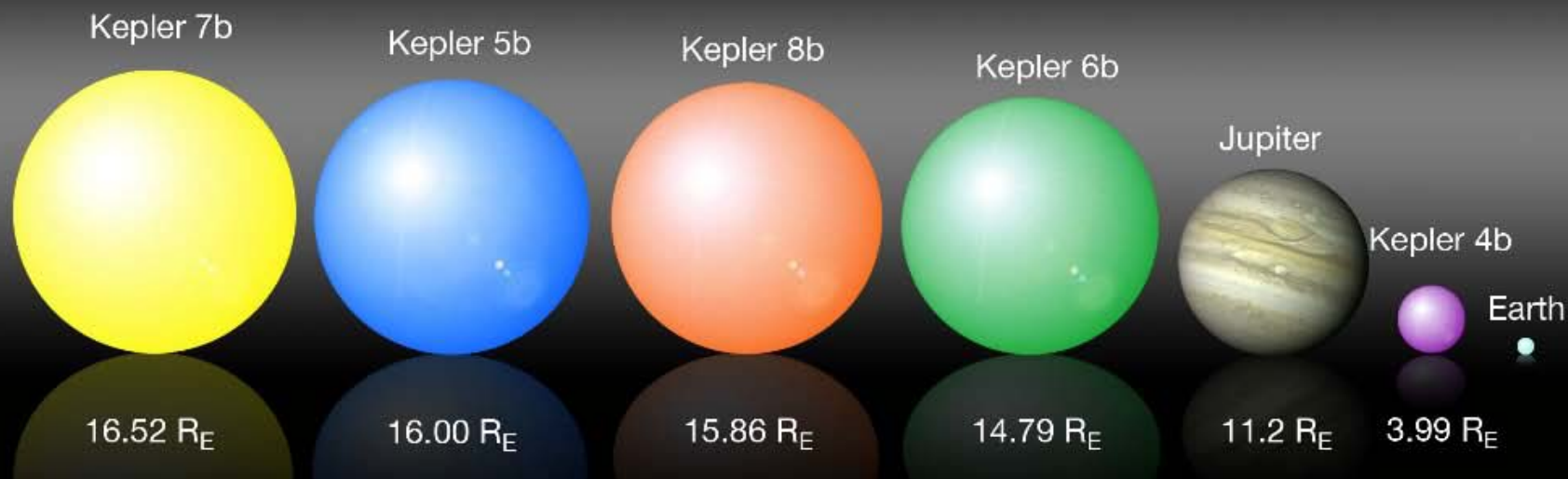
Kepler Spacecraft





Discovery of First 5 Planets reported January, 2010

Planet Size





Surface Optics Corporation Kepler Primary Mirror (1.4 m dia.)





Surface Optics Corporation

Kepler Primary Mirror





Surface Optics Corporation Kepler Primary Mirror





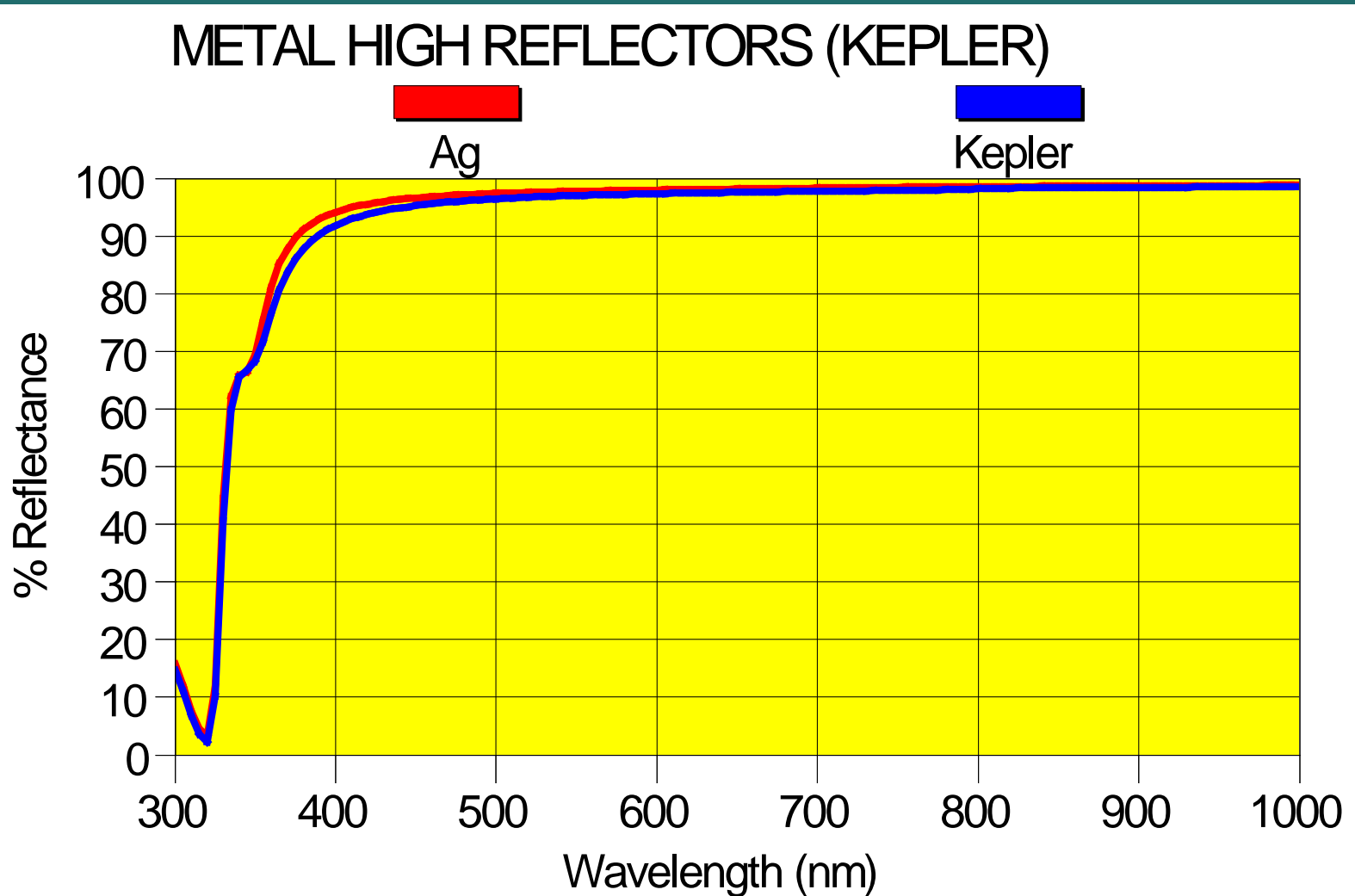
Surface Optics Corporation Kepler Primary Mirror





Surface Optics Corporation

Kepler Primary Mirror





AR Window For NIF at LLNL

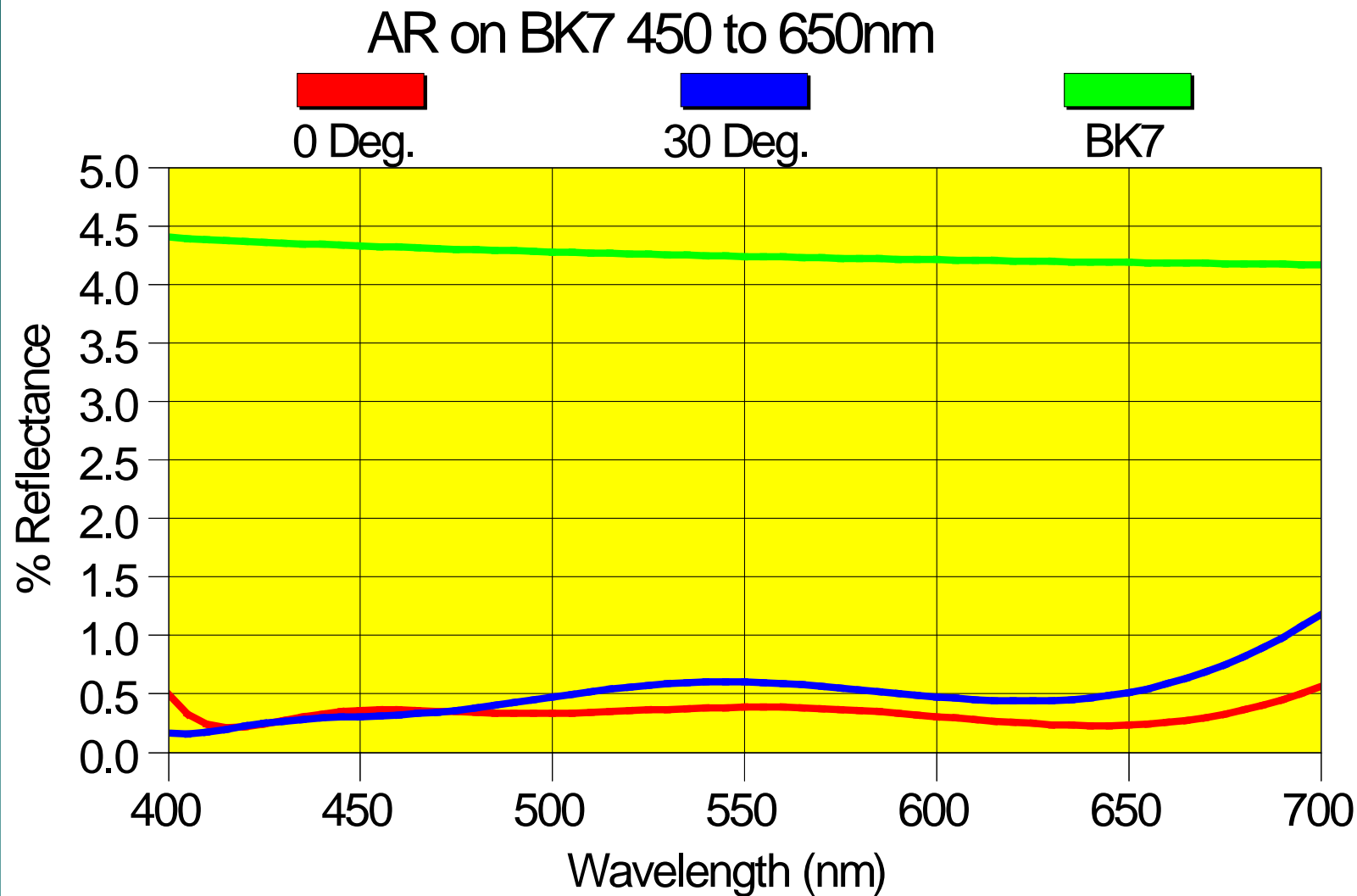


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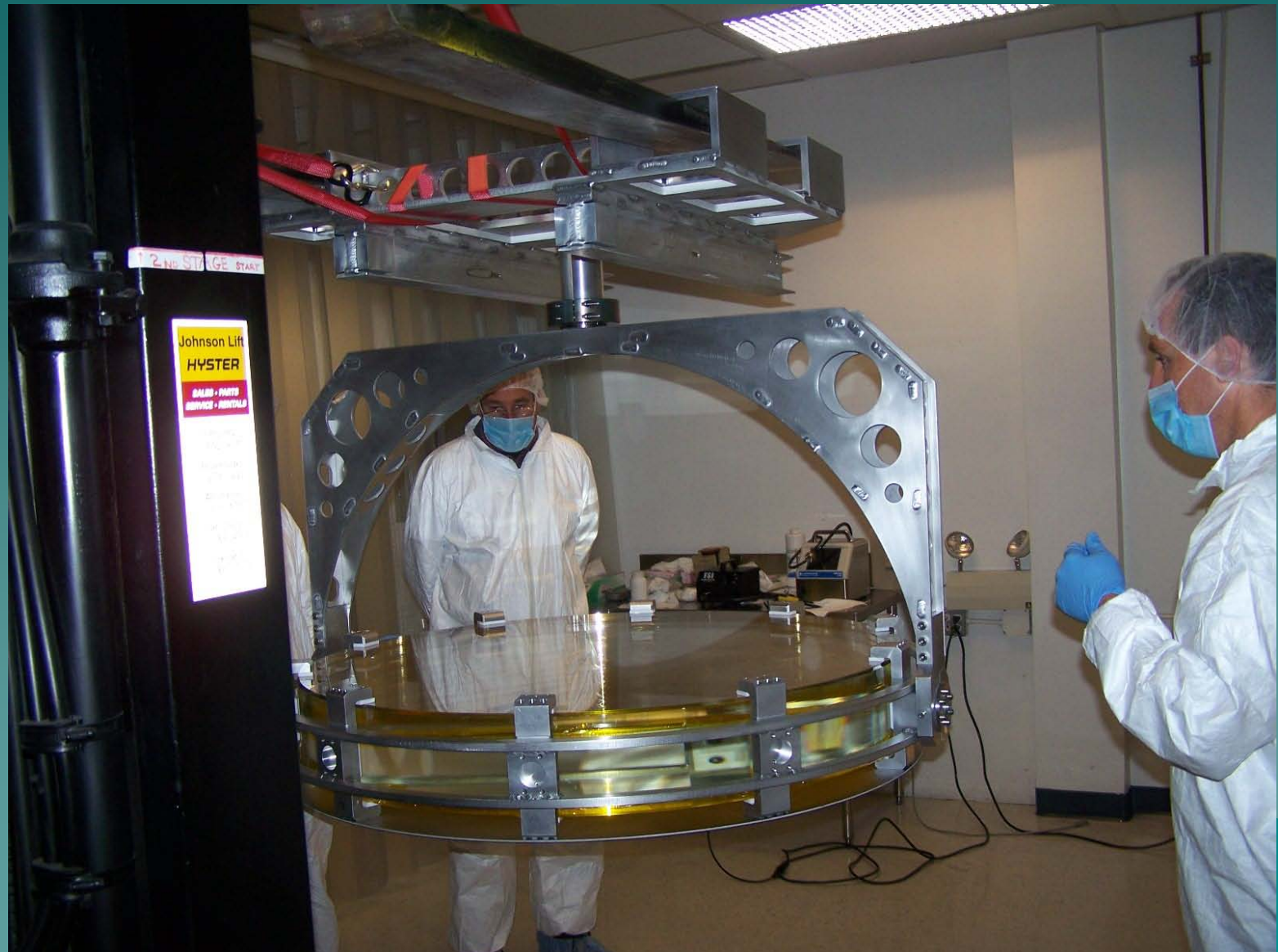
Ta_2O_5 / SiO_2 4 LAYER AR

LLNL Completed on 5/27/10



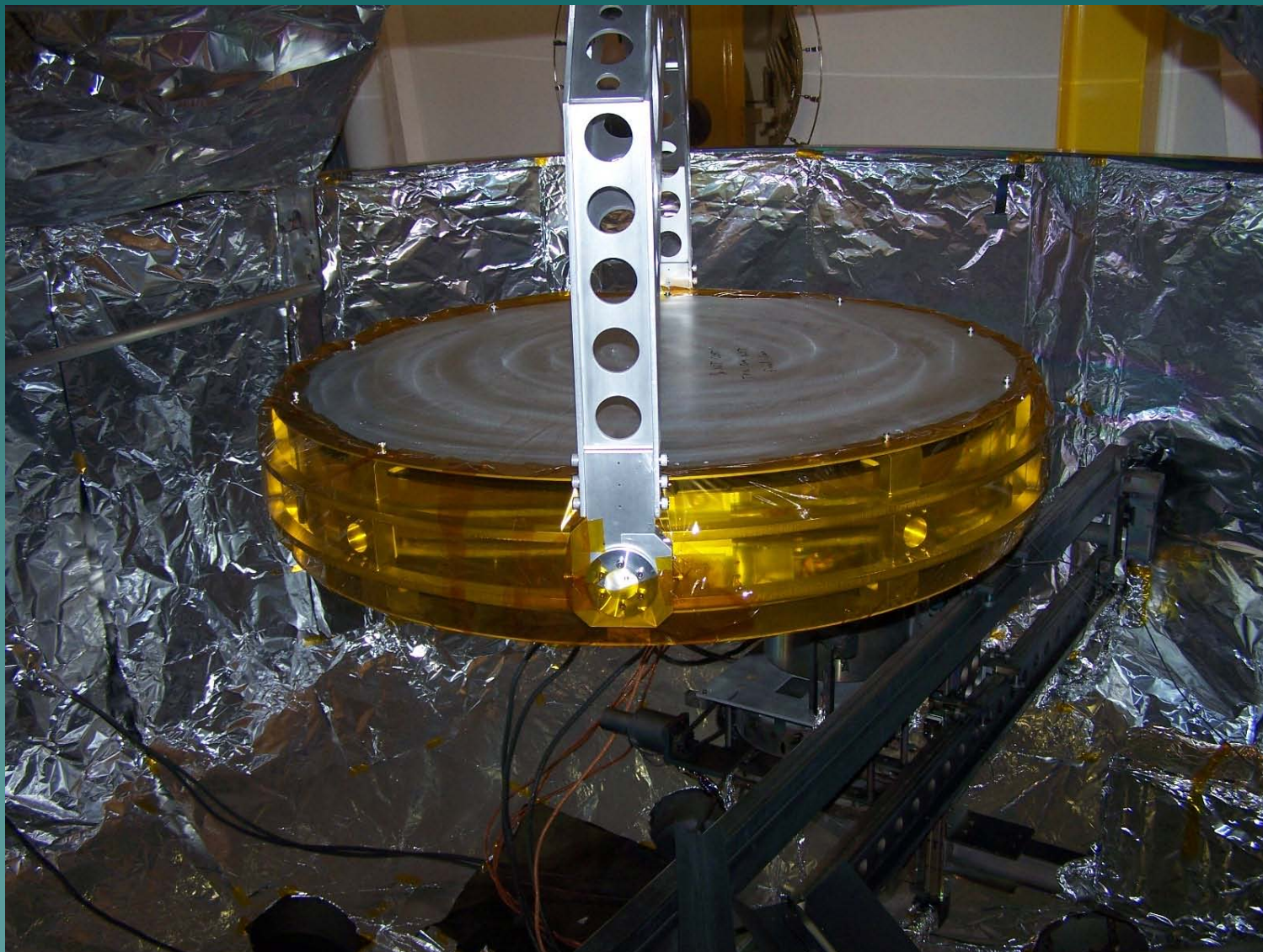


Ta_2O_5 / SiO_2 4 LAYER AR





Ta_2O_5 / SiO_2 4 LAYER AR





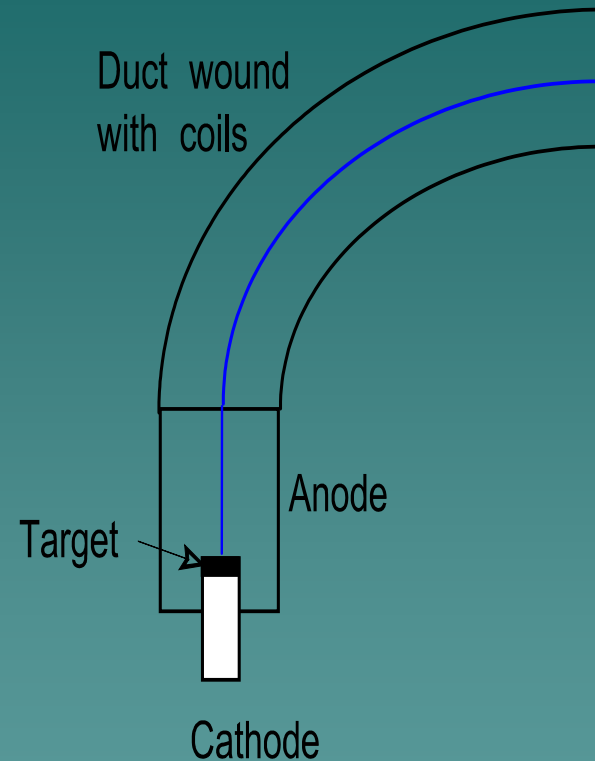
NEW 4-5 Meter Diameter Chamber

- ◆ Needed for Coating Larger Diameter Optical Elements (Customer driven requirement)
- ◆ Multiple Depositions Platforms
 1. Multiple Sources: E-beam; Thermal; Ion Assisted Deposition; Magnetron Sputtering; Filtered Cathodic Arc
 2. Designed to increase useable deposition area
 3. Designed to increase deposition rate
 4. Designed to coating uniformity



The Filtered Cathodic Arc Process

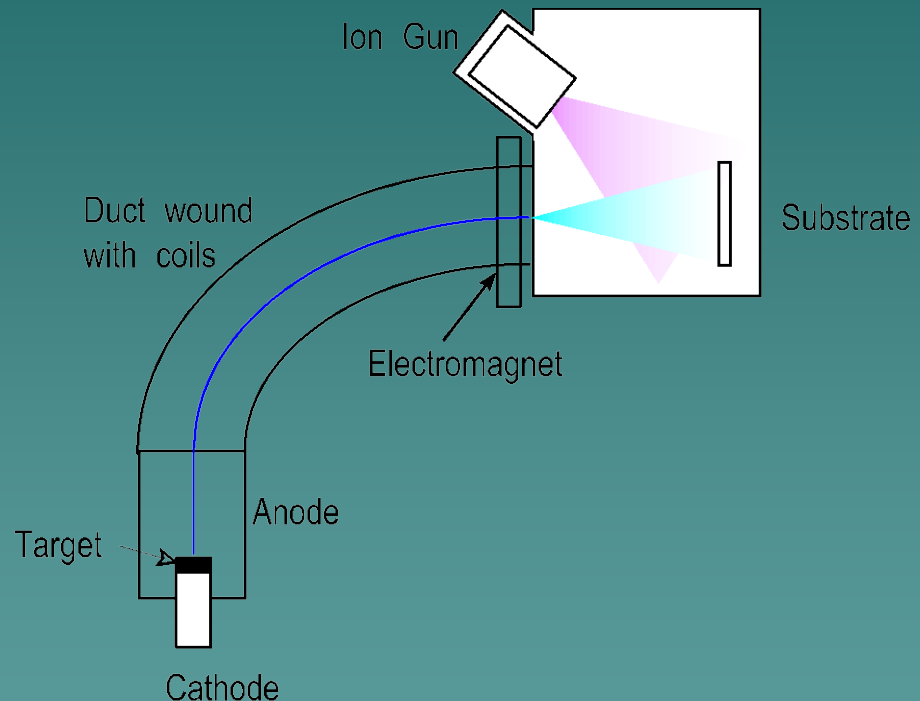
- A low DC voltage-high current supply is used to generate an arc on a water cooled target.
- The arc vaporizes the target material generating high energy ions, neutral atoms and particles.
- The ions are steered by the magnetic and electrical fields through a curved duct.
- Particles and neutrals are filtered by the non-line -of-sight path.





Ion-Assisted-Deposition (IAD)

- The plasma beam is scanned at the exit of the duct by an electromagnet.
- Ions can be accelerated by a substrate bias, permitting well adhered coatings
- Deposition rate $\sim 5 \text{ nm/s per in}^2$ for carbon
- The addition of an End-Hall Ion Source to the Arc Process positively modifies the thin-film properties, increasing adhesion and converting the evaporation material to an oxide, nitride, etc.
- Ambient Temperature Depositions





Freestanding 90° filter (A. Anders)

- ◆ Freestanding coil \Rightarrow
 - High current required (e.g. arc current in series)
 - Openings allow macroparticles to leave the filter volume

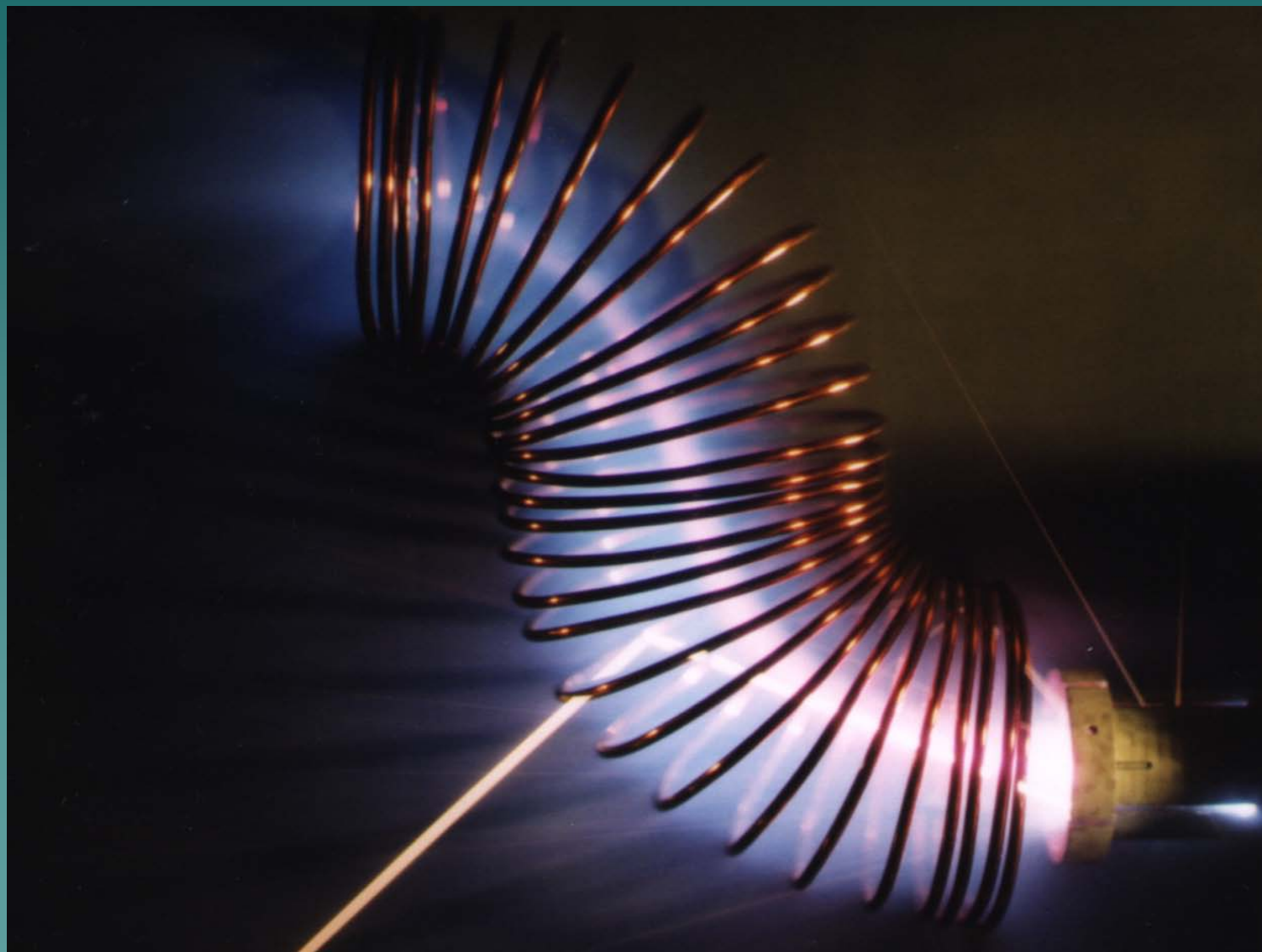


From: A. Anders,
*Surf. & Coat.
Technol.* 93 (1997)
158-167



Freestanding S-filter (A. Anders)

- ◆ Here: arc source is operated with graphite cathode



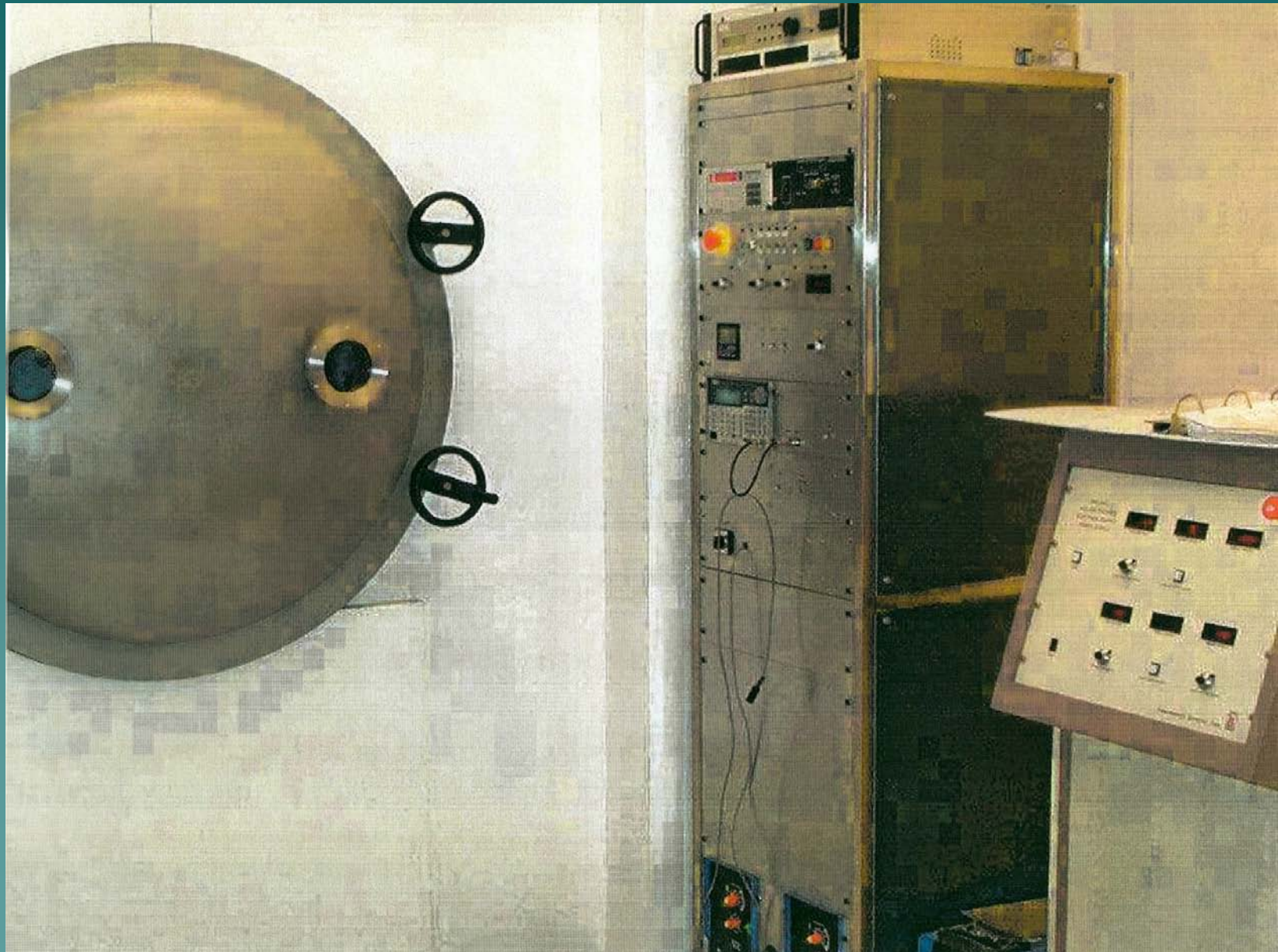


Ion-Assisted Filter Cathodic Arc Deposition (IFCAD)





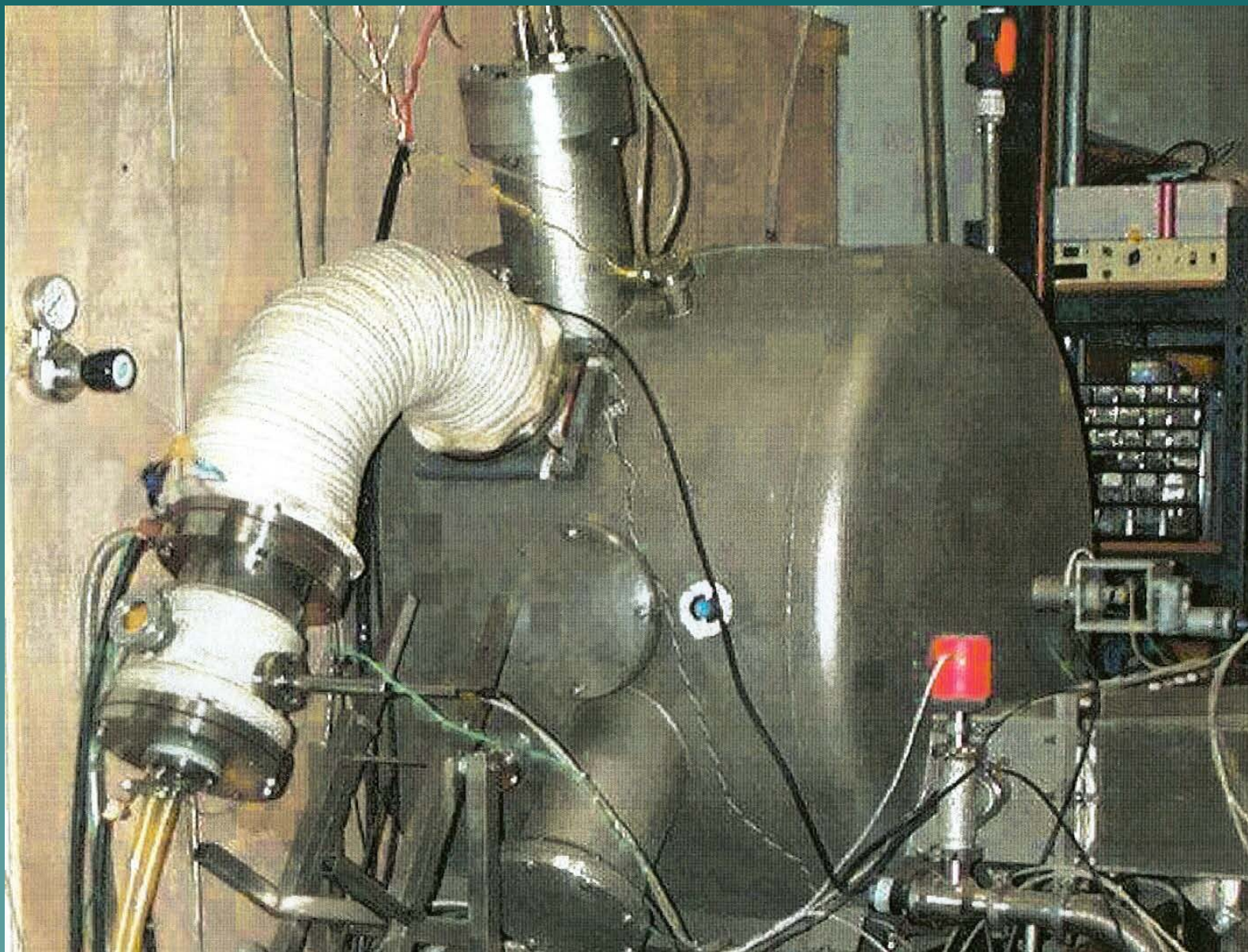
IFCAD: Front of Chamber with Control Panel





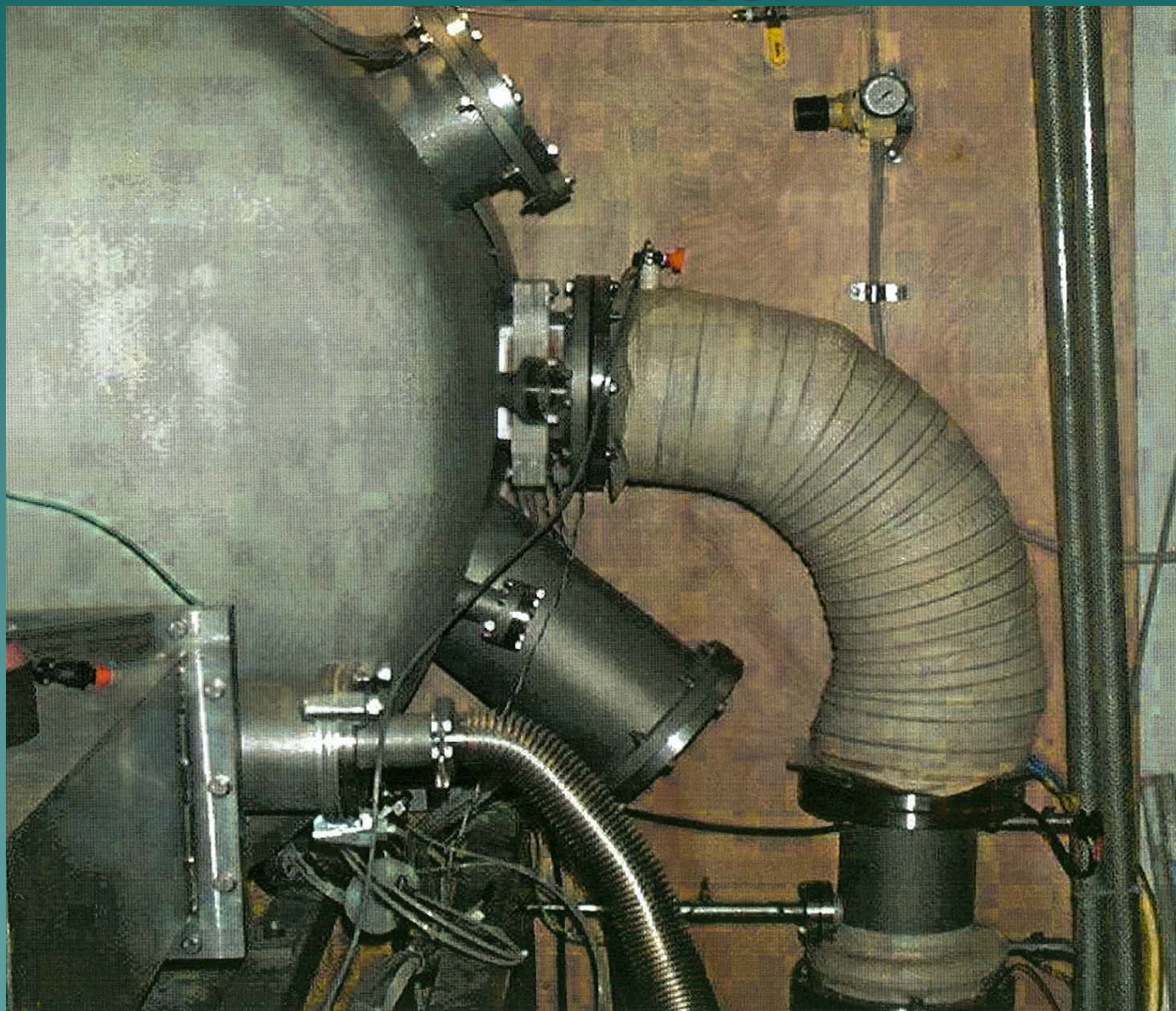
IFCAD: Metal Arc Source with IAD

Source: **Movie**





IFCAD: Carbon Source Attached to Chamber



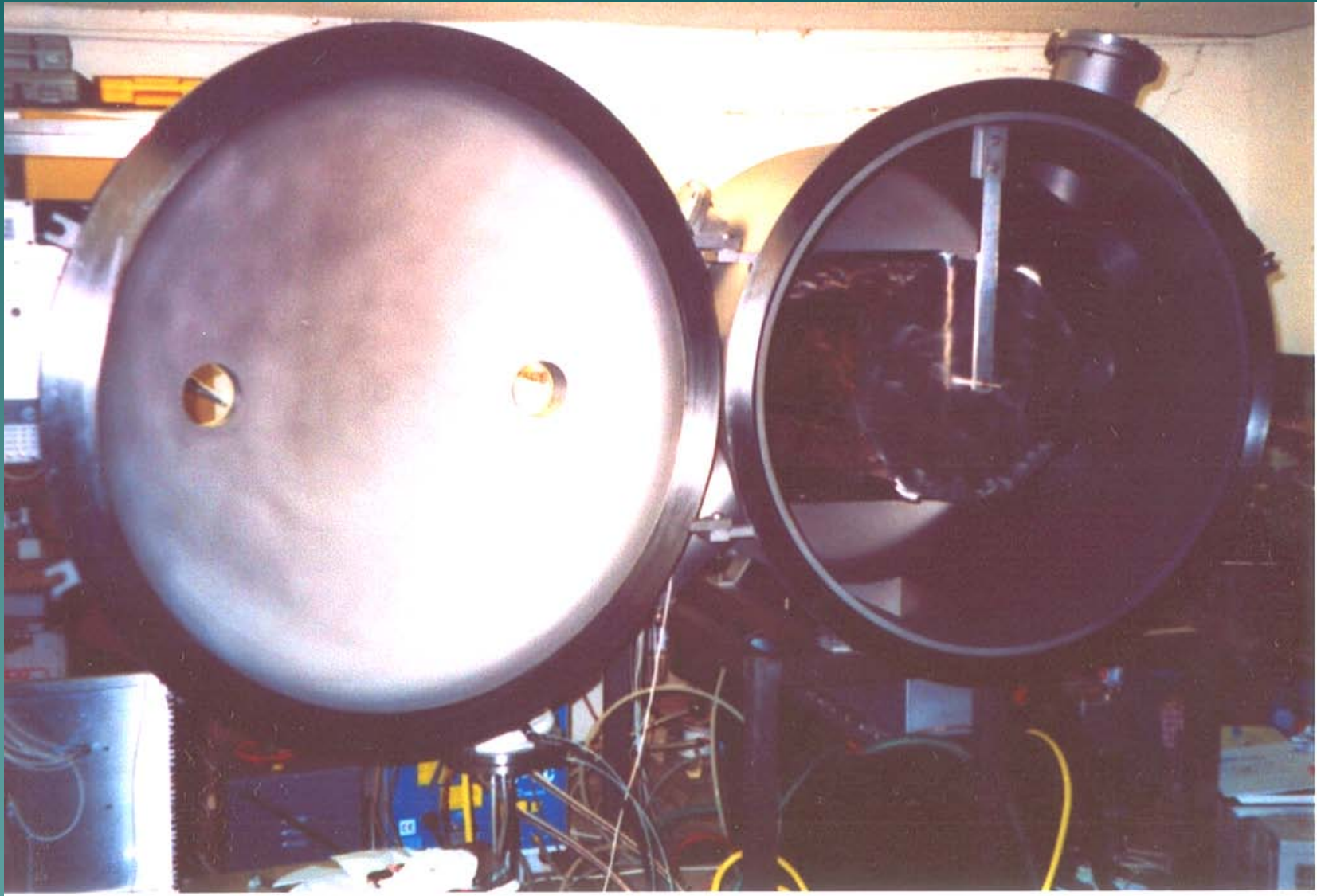


IFCAD: Carbon Ion Beam Entering Chamber





IFCAD: Chamber with Door Open: Drum View





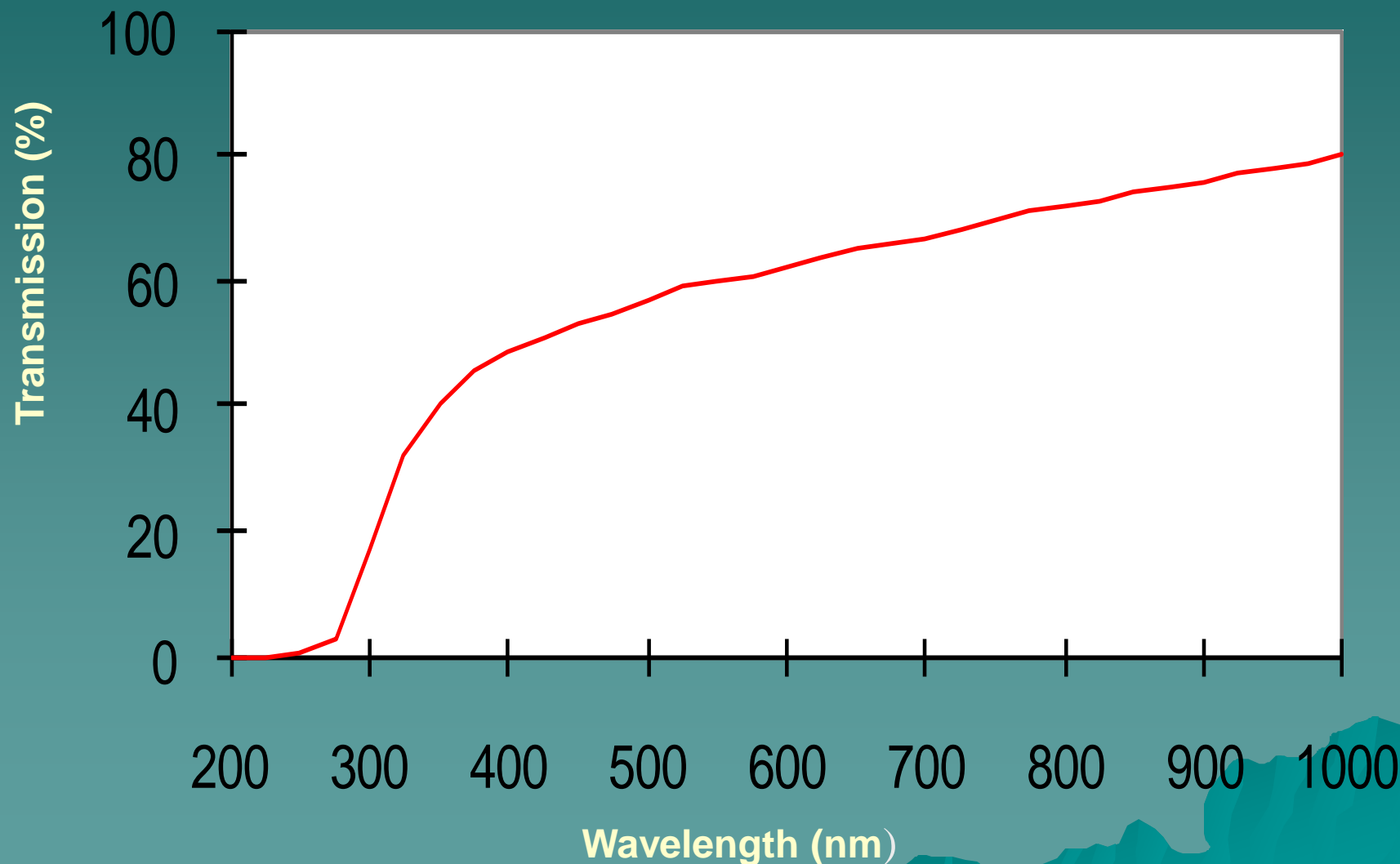
Amorphous-DLC Properties

Property	Nat. Diamond	CVD DLC	DLC (a:CH)	FCA (t:aC)
Hardness GPa	100	80 - 100	10 - 50	70 - 100
Density g/cm ³	3.5	3.2 – 3.4	1.7 – 2.2	3.0 – 3.3
Friction Coeff.	0.1	0.1 (polished)	0.1	0.1
Film Roughness	N/A	3μm	Optically Smooth	Optically Smooth
Adhesion	N/A	Low	Moderate	High
Process T °C	N/A	>600	20 – 325	20 - 150
Structure	Crystalline Sp ³	Crystalline Sp ³	Amorphous mostly Sp ²	Amorphous mostly Sp ³
Reactive Gas	N/A	Yes	Yes	None
Transform T °C	N/A	>600	250 – 350	>500



Optical Performance

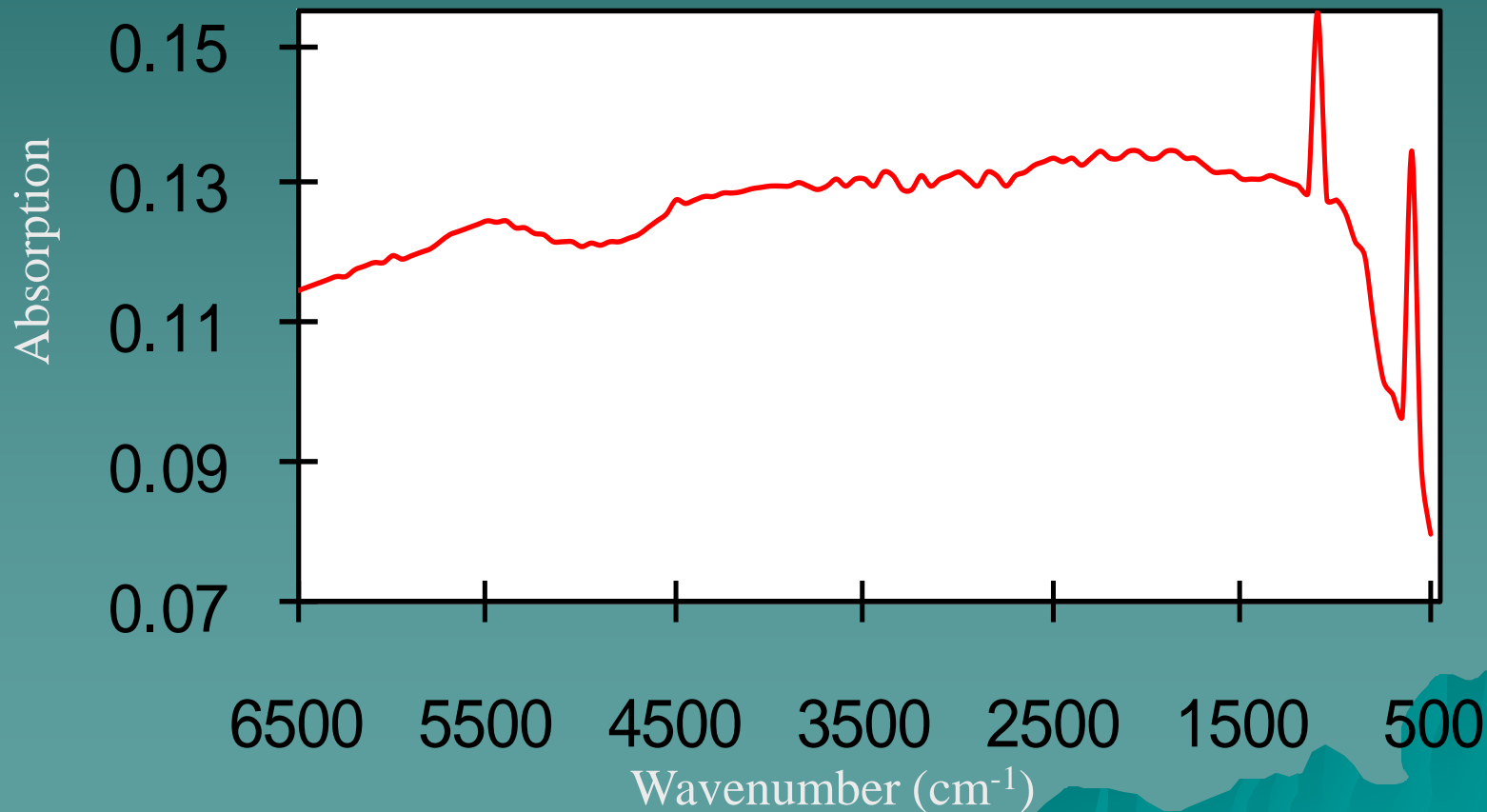
- A-DLC (single layer) exhibits a sharp cut-off in the UV





IR Performance

- A-DLC films are highly transparent in the long wavelength region (1.5 μm to 20 μm) without any absorption peaks caused by C-H bonds (no hydrogen required during deposition)



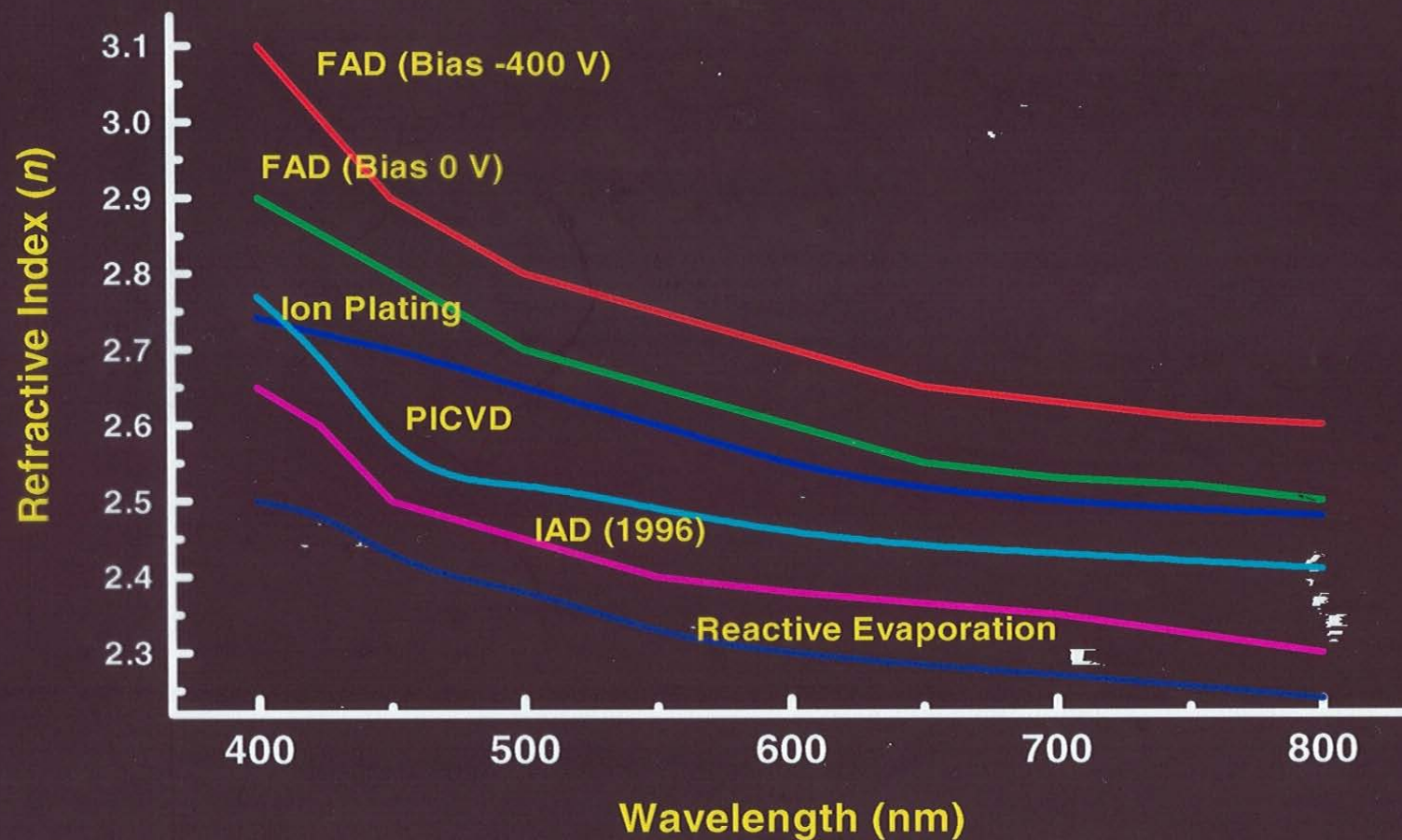


Other IFCAD Materials

- Al_2O_3 clear film of high hardness
- Ta_2O_5 optical coating material (2.1n)
- TiO_2 high index optical coating material (>2.6 n)
- AlN purple decorative film
- TiN hard reddish gold wear resistant film
- TiCN dark gray and hard wearing
- CrN dull gray with low coefficient of friction
- ZrN brass colored film with good corrosion resistance
- ITO transparent conductive thin-film
- C_3N_3 material exhibiting extreme hardness (potentially)

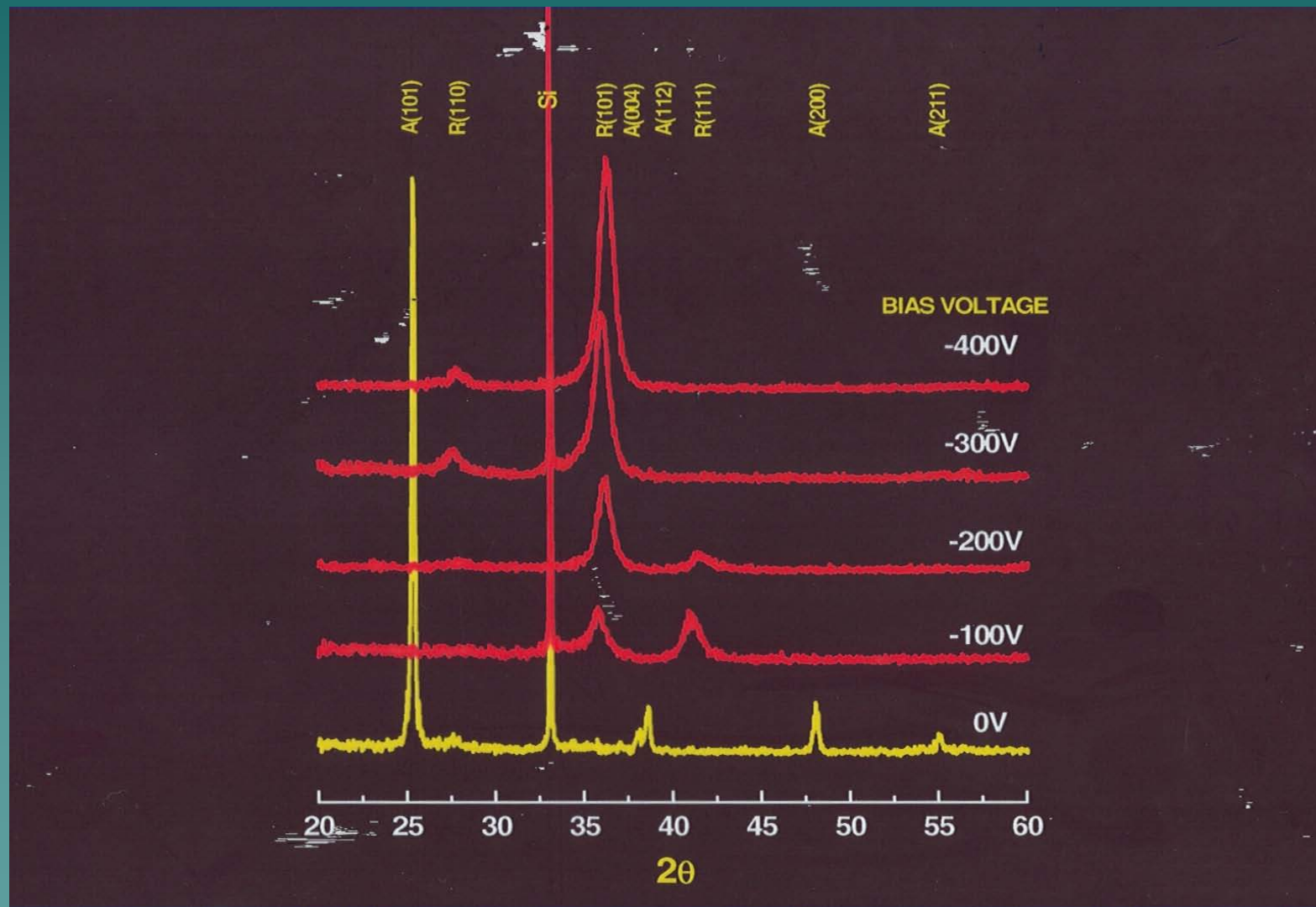


TiO₂: Produced by Energetic Processes (P. Martin)





TiO₂: X-Ray Diffraction vs Substrate Bias Voltage (P. Martin)





Out-of-Plane, Double-Bend Filter

- ◆ Out-of-plane S-filter from Nanyang Technical University

- ◆ Commercial version:

- Hard Disk Drives
- Reading Heads:
 - **Samples**

- ◆ Nanofilm Technologies International Pte. Ltd.





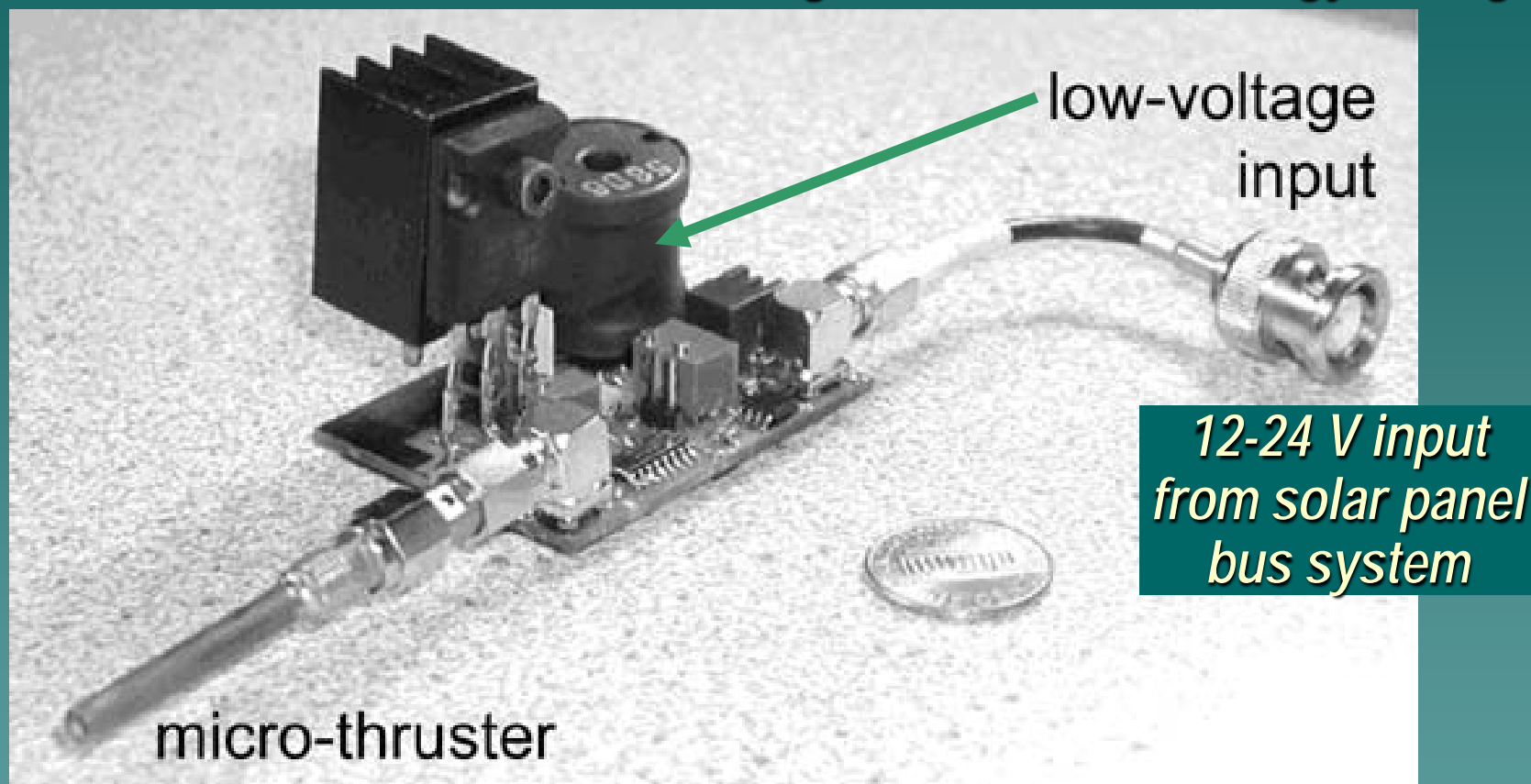
Future Outlook for Space-Based Deposition Technology

- Lunar-Mars Proposal (January 14, 2004) **CHANGED**
- Moon used as a Temporary Stop for Voyages to Mars
- Lightweight Deployable Structures for Space Power
- Space-Based Depositions for Large Area Telescopes
- Lunar Vacuum: 5.0×10^{-13} Torr
- Low Earth Orbit: Not Suitable for Metal Film Depositions
- (LEO) Atomic Oxygen Fluence: 2.3×10^{20} atoms/cm²
- Filtered Cathodic Arc: Simple Process for High Quality Thin-Film Deposition



Light-Weight Pulsed CA Source

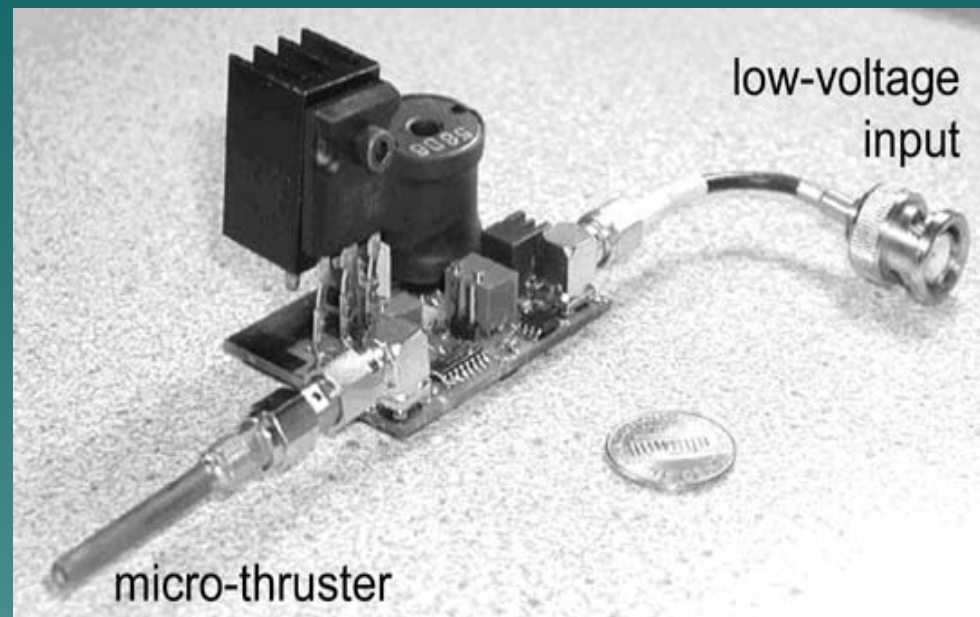
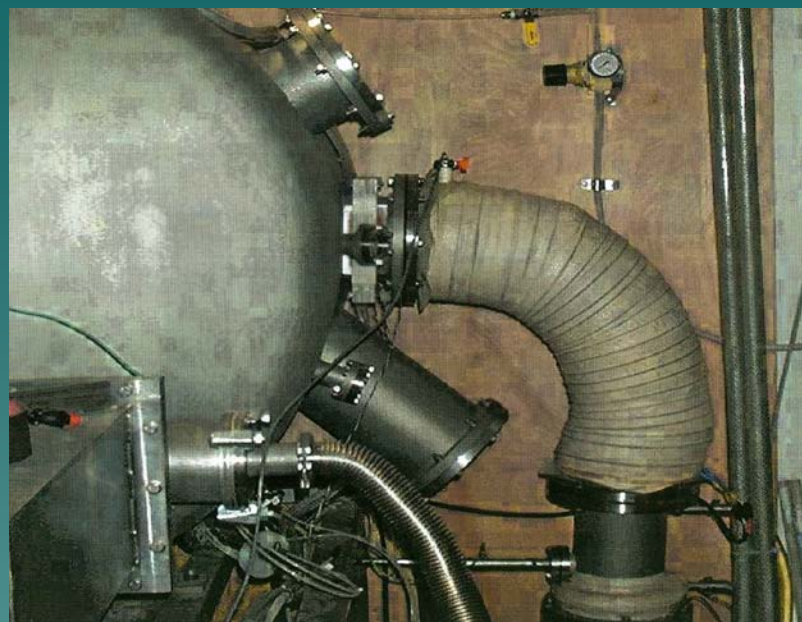
Use of low voltage and inductive energy storage



PULSED cathodic arc can readily be miniaturized, for example as "microthruster," used to correct the orbit of satellites



Weight Reduction of the Deposition System



~ 500 kg



~ 100 g

- ◆ *Weight of arc source, filter, and power supply < 300 g (!)*
- ◆ *Vacuum is "free"*
- ◆ *Cathodic arc does not need any process gas*



Future Work on Space-Based FCAD Technology

- No Free Lunch: the price of miniaturization is relatively slow deposition speed for large areas. **This is OK!**
- Robotic Control Design for In-Vacuum Large Area Terrestrial Depositions—time of deposition is not a critical. **Vacuum is Free in Space.**
- Design and Testing of miniaturized FCA source with continuous source material feed: Teaming with LBNL to develop this enabling technology for future space missions.
- NASA had announced plans to send man missions to the far side of the moon: this technology could play a vital part in the future of space exploration.

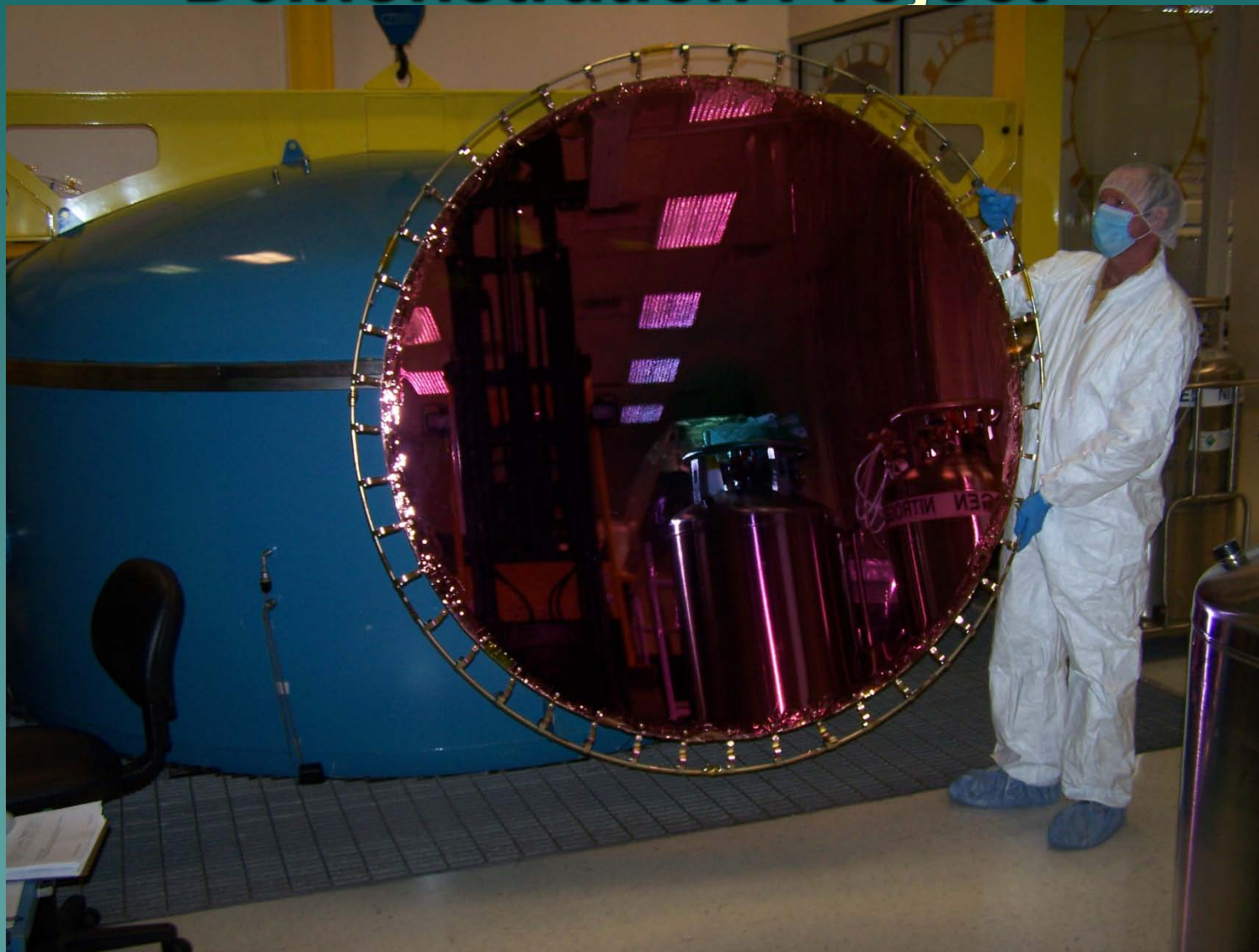


Technology will be best used on the Lunar Surface



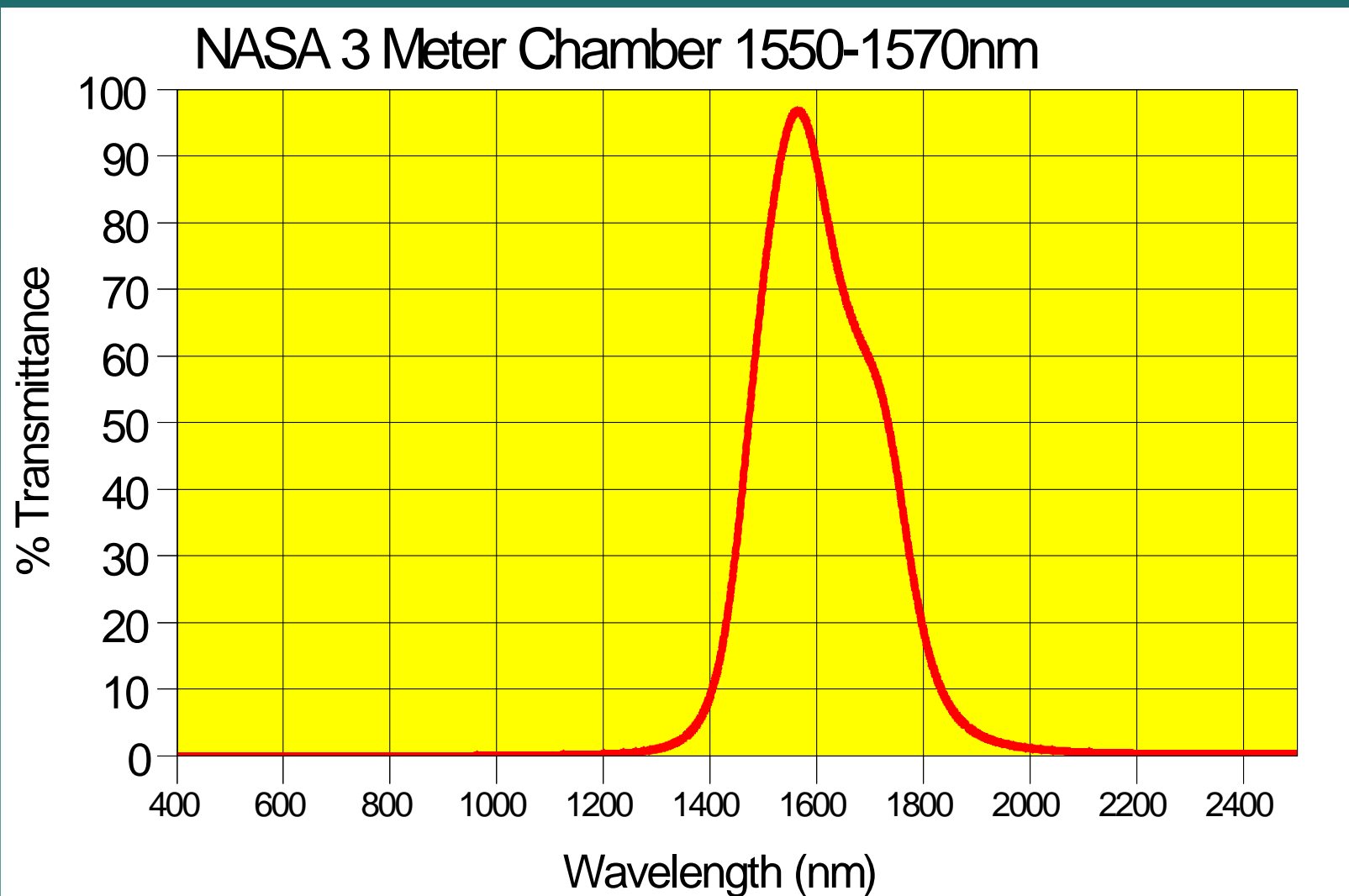


Mars Laser Communications Demonstration Project





Mars Laser Communications Demonstration Project





Large Area Reflector on Polymeric Substrates





Thirty Meter Telescope Project





Surface Optics Corp: Future Work

- ◆ SOC is continually developing coating capabilities for advanced optical coatings on temperature-sensitive substrates and large scale optical applications.
- ◆ Uniformity across large area substrates is being improved by upgrades in the computer control and thickness monitoring system for the translating deposition platform.
- ◆ Plans to Build an Even Larger Chamber (4-5 meter) with more Powerful Deposition Capability: incorporating FCA and Sputtering
- ◆ SOC is working to improve the polymeric coating process for new flexible space power systems.



Surface Optics Corp.

Thank you for your attention!

More information available at:
surfaceoptics.com and ionbeamoptics.com

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